PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

22-26 September 2025
Antibes, French Riviera

FINAL PROGRAM & EXHIBITORS GUIDE

ORGANIZED BY SFV Société Française du Vide

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INNOVATIVE COATING SOLUTIONS

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01 SOLUTIONS FOR COMPLEX SURFACES & SYSTEMS

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Coating Services
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Surface Characterization
- Advanced analysis capabilities

02 ADVANCED COATINGS ON POWDERS

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- Tailored surface properties for industry-ready applications

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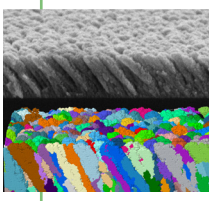

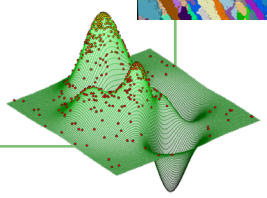

Discover how ICS expertise can elevate your coating results and operations.

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PLASMA THIN FILM INTERNATIONAL UNION MEETING

22 – 26 September 2025

Antibes, French Riviera

www.plathinium.com

19 rue du Renard - F-75004 Paris, France

Legal Deposit: September 2025

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WELCOME

The PLAsma THIN film International Union Meeting (PLATHINIUM) is a biennial scientific conference that provides a unique forum for exchanging knowledge in the fields of low-temperature plasmas and thin films. It offers tutorials for students and fosters synergies between academia, research, and industry.

PLATHINIUM was created in 2019 through the merger of three former events - CIP (International Colloquium on Plasma Processes), ITFPC (Innovation in Thin Film Processing and Characterization), and MIATEC (Magnetron, Ion and Arc Technology) - and is now on its 4th edition. Today, it stands as a recognised meeting that emphasising both established and emerging applications, including thin films and coatings for microelectronics, automotive, and aeronautic industries, as well as the use of plasmas, thin films, and nanostructures in environmental, energy, biomedical, and agricultural domains.

PLATHINIUM 2025 takes place in Antibes, continuing the tradition of being a leading venue for advancing low-temperature plasma and thin film science and technology.

The 2025 scientific program will cover the following topics:

- **AMELI** / Plasma and/in liquids interaction: fundamentals and applications, plasmas for agriculture, bio-medicine, environment, green chemistry
- **DEPOS** / Plasma-assisted deposition, coatings and layers: fabrication process, characterizations, optical, electrical, tribological, catalytic and others applications
- **GROM** / Thin film growth and modelling (for plasma and others processes) including new data science and artificial intelligence approaches
- **ITEC** / Innovative applications, solutions and technologies (industrial, startup)
- **MODIDD** / Modelling, diagnostics and data-driven optimization of plasma processes: plasma modelling, processing, and diagnostics (optical, electrical, and laser-based diagnostic techniques and innovative data processing approaches (artificial intelligence, large language models (LLM), and digital twins) for low and high-pressure plasmas, as well as laser-produced plasmas and various discharge types (DC, RF, MW, DBD)
- **NANO** / Plasma nanotechnologies: nanomaterials, nanostructured thin films, dusty and misty plasmas, nucleation and growth...
- **PSURF** / Plasma surface processing, plasma etching, atomic layer processing, surface nanostructuration, surface functionnalization

Have a fruitful event and a pleasant stay in Antibes and the French Riviera!

Welcome at 4th PLATHINIUM!

Vasco GUERRA
Chair of the Scientific Committee

Corinne CHAMPEAUX
Chair of the Steering Committee

PLATHINIUM
PLASMA THIN FILM INTERNATIONAL UNION MEETING

TABLE OF CONTENT

GENERAL INFORMATION

Practical information

- **Official language**

The conference language is English.

- **Wi-Fi access**

Indicated on your badge provided onsite.

- **Badges**

All delegates, exhibitors and visitors must wear their badges at all times to obtain admittance to the conference venue.

- **Mobile phone**

Please keep your mobile phone turned off or in silent mode in all conference rooms.

- **Publication**

The final program and the abstract book are sent in PDF to all registered participants via a download link.

- **Tourism Office**

Antipolis Convention Centre – level 1
60 chemin des Sables
06160 Juan-les-Pins

Phone: +33 (0)4 22 10 60 01 (press 1)
www.antibesjuanlespins.com/en

- **Opening hours**

Welcome desk – level 2

Monday 22 Sept	08:30 – 20:00
Tuesday 23 Sept	08:30 – 20:00
Wednesday 24 Sept	08:15 – 18:30
Thursday 25 Sept	08:15 – 18:00
Friday 26 Sept	08:15 – 12:00

Exhibition – level 2

Tuesday 23 Sept	09:30 – 20:30
Wednesday 24 Sept	09:00 – 18:30

Disclaimer

The program is preliminary. The organizers reserve the right to alter the program if and as is deemed necessary.

The PLATHINIUM 2025 organization and/or its agents have the right for any reason beyond their control to alter or to cancel, without prior notice, the Conference or any of the arrangements, timetables, plans or other items relating directly or indirectly to the Conference. The PLATHINIUM 2025 organization and/or its agents shall not be liable for any loss, damage, expenditure or inconvenience caused as a result of such alteration or cancellation.

Contacts

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gweltaz.hirel@vide.org

Hervé LEMOINE
Exhibition coordinator
herve.lemoine@vide.org

SOCIAL EVENTS

Get together parties

✓ Included in the registration – no booking necessary

- **Welcome reception**

Monday 22 September – 18:30 - 20:00

On Monday evening, after the short courses, come to pick your badge and conference material. The organization offers a cocktail to get together over a drink with other attendees.

- **Poster party session #1 and Industrial evening**

Tuesday 23 September – 17:30 - 20:30

At the end of the first day of the conferences, during the Poster session #1, all the exhibitors will be pleased to welcome you with a dinner cocktail.

- **Poster party - session #2**

Wednesday 24 September – 17:35 - 18:30

Finish the last but one day relaxed: after the afternoon break, let's talk with the presenters, of the poster session #2, about their work while having a friendly drink.

- **Conference dinner cocktail**

Thursday 25 September – 19:30 - 22:30

Enjoy a relaxed moment during the cocktail reception offered on the 3rd floor of the Palais des Congrès with its panoramic terrace and a musical entertainment

Social activities

Friday 26 September from 14:00
✓ *Included in the registration / Booking mandatory*

- **Option #1 - Excursion to Grasse**
  International capital of Flowers and Perfume

  - 14:00 / Transfer by bus from to Grasse
  - 15:00 / Guided tour of the Fragonard Perfume Factory
  - 16:15 / Guided tour of Grasse old town
  - 17:45 / Transfer back to Juan-les-Pins

The town of Grasse is said to be the core of the Riviera as well as a model of Provençal culture. The city offers splendid vistas over the shores near Cannes. A “Cité d'Art & d'Histoire,” Grasse is known as the “Capital of Flowers and Perfume.” Clinging to sun drenched hills, this place slowly reveals its charms to those who linger in its picturesque alleyways and welcoming little squares. The historic centre confirms this architectural quality. In the 18th century, perfume making, which took over from the tanneries, blossomed. In the 19th century, flower cultivation and perfume production gave Grasse its international reputation. You will visit one of the oldest perfume factories established in a 19th century building in the heart of the old town where perfumes and soaps are crafted everyday.

- **Option #2 - Walking tour on the coastal path “sentier de Tire-Poil”**
  Immerse in the nature of the Cap d’Antibes

  - 14:00 / Transfer from the Congress site to a bus tour around the Cap d’Antibes
  - 14:45 / Hiking on the coastal path
  - 17:15 / Transfer back to Juan-les-Pins

Discover with a guide the landscapes, the points of view and the remarkable species of the Tire-Poil path. Sea Lavendar, Jupiter Beard, Common Tern… these are the suggestive names which indicate the natural wealth of this little paradise on the Mediterranean coast. You will meet native and exotic plants and will learn to respect the protected species present on the Cap d’Antibes. A naturalistic, educational, playful and sports activity for everybody!

PROGRAM INFORMATION

Codes & topics

In the scientific program, the PLATHINIUM conference has been organized around 7 topics:

AMELI **Plasma and/in liquids interaction:**
fundamentals and applications, plasmas for agriculture, bio-medicine, environment, green chemistry (decontamination/sterilization, depollution, gas conversion, bio-medical, treatments…)

DEPOS **Plasma-assisted deposition, coatings and layers:**
fabrication process, characterizations, optical, electrical, tribological, catalytic and others applications

GROMThin films growth and modelling *(for plasma and others processes) including new data science and artificial intelligence approaches*

ITEC **Innovative applications, solutions and technologies**
(industrial, startup)

MODIDDModelling, diagnostics and data-driven optimization of plasma processes: *plasma modelling, processing, and diagnostics (optical, electrical, and laser-based diagnostic techniques and innovative data processing approaches (artificial intelligence, large language models (LLM), and digital twins) for low and high-pressure plasmas, as well as laser-produced plasmas and various discharge types (DC, RF, MW, DBD)*

NANOPlasma nanotechnologies: *nanomaterials, nanostructured thin films, dusty and misty plasmas, nucleation and growth…*

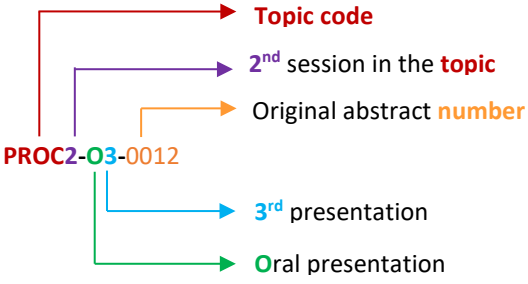
PSURF Plasma - surface processing, *plasma etching, atomic layer processing, surface nanostructuration, surface functionnalization*

Key to lecture

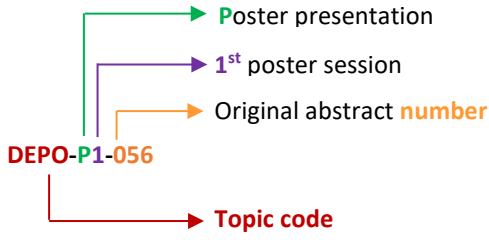
- **Type of presentations**

PL	Plenary talk	O	Oral presentation
K	Keynote lecture	P	Poster presentation

- **Lecture numbers**



- **Poster numbers**



Instructions for authors

- **Oral Presentations**

  Durations (including discussions)

  - Plenary talk 40 minutes
  - Keynote Lectures 30 minutes
  - Oral Presentations 20 minutes

  Lectures must be presented **in English.**

  Each speaker must ensure that presentation (including 5 min for questions) is not longer than stipulated in the program. The chairpersons will be strict on timing.

  There is no preview system for the conference. All speakers have to **load their presentation file on the laptop available on the session room, preferably on the half day before the start in the session room.**

  PowerPoint projection will be available in the session rooms which are equipped with a laptop computer and a projector. Overhead projection and slide projection are not available. All the hardware will be provided by the Congress to ensure consistency in technical quality and allow for quick and smooth transition between the speakers.

  Please note that **only the computers provided on site can be used**.

  The video files attached to the presentation must be located in the same folder as the presentation files.

  Presentation's Privacy: at the end of the Congress, ALL presentations and associated fills will be deleted.

- **Poster Presentations**

  Each poster must be in the size of **0.85 m in width and 1.2 m in height (A0).**

  The author's name and affiliation and the title of the paper must be indicated in the top section of the poster.

  The posters will be presented and numbered according to the poster programme. The poster number will be displayed on top of the board. Writing or painting on the poster board is not allowed.

  All posters will be displayed from Tuesday to Thursday evening.
  However, focus will be made with 2 poster sessions on:

  - **P1 / Session #1** with industrial evening / Tuesday 23 from 17:30 until 19:30
  - **P2 / Session #2** with refreshments / Wednesday 24 from 16:35 until 18:30

  Presenters are expected to be next to their poster during the session (P1 or P2) assigned to their poster (information sent by email & available on the detailed program & registration space).

  Posters should be mounted from Tuesday 23 September 2025 at 10:00 and should be removed by 18:00 on Thursday 25 September 2025.

Invited lectures

- **Plenary speakers**

In ANTIPOLIS AUDITORIUM

Jones ALAMI **PL6 // THU 25 – 14:00**
Mohammed VI Polytechnic Univ. (MA)
Tackling Lithium-ion battery challenges with PVD technologies

Marcela BILEK **PL5 // THU 25 – 8:40**
Univ. Sydney (AU)
Plasma technologies advancing biomedicine and sustainability

Mariadriana CREATORE **PL2 // TUE 23 – 14:00**
Univ. Eindhoven (NL)
On novel merits of (plasma-assisted) atomic layer deposition for next-generation energy applications

Olivier GUAITELLA **PL7 // FRI 26 – 08:40**
LPP, Ecole Polytechnique, Palaiseau (FR)
Plasma-catalyst interaction mechanisms for CO_2 recycling and molecule conversion

Amanda LIETZ **PL3 // WED 24 – 8:40**
NC State Univ., Raleigh (US)
Plasma responses to tailored voltage waveforms in capacitively coupled plasmas

Ryo ONO **PL4 // WED 24 – 14:00**
Univ. Tokyo (JP)
Fundamental diagnostics and modeling for streamer discharge and its application for cancer treatment

Mohan SANKARAN **PL1 // TUE 23 – 09:25**
Univ. Illinois, Urbana Champaign (US)
Plasmas for ultrawide bandgap materials

▪ Keynote speakers

Agnès GRANIER
Univ. Nantes (FR)

ELLA FITZGERALD ROOM
NANO2-K1-010 // FRI 26 – 10:35

Optimisation and in situ control of the deposition of nanocomposite thin films in low pressure misty plasma

Satoshi HAMAGUCHI
Univ. Osaka (JP)

ELLA FITZGERALD ROOM
PSURF2-K1-090 // TUE 23 – 16:15

Numerical simulations and ion beam experiments for the analyses of surface reactions for reactive ion etching

Rony SNYDERS
Univ. Mons (BE)

ANTIPOLIS AUDITORIUM
ITEC3-K1-125 // FRI 26 – 10:35

Study of CH4 pyrolysis in a planar atmospheric gliding arc discharge

Anne-Lise THOMANN
Univ. Orléans (FR)

ANTIPOLIS AUDITORIUM
GROM2-K1-045 // TUE 23 – 16:15

Metal thin films growth by magnetron sputter deposition in He: numerical and experimental approach

Finalists for the SFV Michel Cantarel Student Grants

Yanis AGHA ELLA FITZGERALD ROOM
LSPM, Univ. Sorbonne Paris-Nord, Villetaneuse MODIDD2-O2-093 // WED 24 – 10:55
Description of H-atom absolute densities and sub-ns decay times in a pulsed microtube plasma jet using ps-TALIF and a streak camera

Aryan ARYAN ELLA FITZGERALD ROOM
GREMI – ICMN, Univ. Orléans (FR) NANO1-O1-028 // THU 25 – 16:55
DC plasma-inducted phase and morphological evolution of PtSn and PtRuSn nanoparticles produced in a magnetron-based gas aggregation source

Salah-Eddine BENRAZZOUQ ANTIPOLIS AUDITORIUM
IJL, Univ. Lorraine, Nancy (FR) DEPO1-O4-123 // TUE 23 – 11:35
From temperature-independent to tunable resistivity of high-entropy alloys thin films

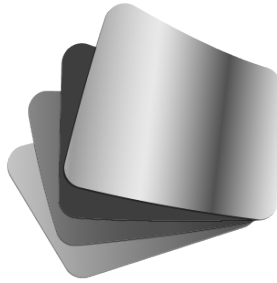
Robin DANTINNE ANTIPOLIS AUDITORIUM
ChIPS, UMons (BE) PSURF5-O2-114 // THU 25 – 15:05
Elucidating the growth mechanism of functionnalized plasma polymer films using complex geometry substrates at various substrate temperatures

Mina FARAHANI ELLA FITZGERALD ROOM
Univ. West. Bohemia, Pilsen (CZ) MODIDD3-O2-054 // THU 25 – 15:05
Enhancing energy flux to insulating surfaces using unipolar and bipolar HiPIMS pulse configurations

Marion GIREAU ELLA FITZGERALD ROOM
IRCER, Univ. Limoges (FR) NANO1-O3-086 // THU 25 – 17:35
Novel nanocomposite thin films by pulsed laser processes for plasmonic based sensing of cancer markers

Marianna ROGGIO ANTIPOLIS AUDITORIUM
CNR-NANOTEC, Univ. Bari (IT) DEPO6-O4-120 // THU 25 – 17:15
Atmospheric pressure plasma-assisted deposition of zinc-based coatings for agriculture applications

Leila ZAHEDI ANTIPOLIS AUDITORIUM
CEPLANT, Masaryk Univ, Brno (CZ) PSURF5-O1-007 // THU 25 – 14:45
Enhancing corrosion resistance of magnesium alloys with plasma treatment and electrospun biodegradable polymer coatings



PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

DETAILED PROGRAM

- Tuesday 23 September
- Wednesday 24 September
- Thursday 25 September
- Friday 26 September

Tuesday 23 September

9:10 – 12:30

9:10 Opening ceremony — ANTIPOLIS AUDITORIUM
V. Guerra, *Chair of Plathinium 2025*
C. Champeaux, *Chair of the Steering Committee of Plathinium 2025*

9:25 **PLENARY TALK //** Plasmas for ultrawide bandgap materials
M. Sankaran
Univ. Illinois, Urbana-Champaign (US)

10:05 COFFEE BREAK

DEPO 1 Plasma-assisted deposition, coatings and layers

ANTIPOLIS AUDITORIUM

Chair: D. Hegemann (CH)

10:35 DEPO1-O1-077 ● Minimizing the impact of negative oxygen ions on aluminium-doped zinc oxide thin films deposited by rotatable RF magnetron sputtering
L. Villibord, E. Stamate
Technical Univ. Denmark Nanolab - Lyngby (DK)

10:55 DEPO1-02-031 ● Controlling the stoichiometry of copper oxides depending on operating parameters
Y. Wang, F. Arefi-Khonsari, A. Pailleret, J. Pulpytel
Sorbonne Univ., CNRS, LISE, Paris (FR)

11:15 DEPO1-O3-023 ● Exploring energy transfer in sputter deposited tungsten films: effects of magnetic field strength and pressure-distance on phase composition
F. Ahangarani Farahani, D. Depla
Department of Solid State Sciences, Ghent Univ., Gent (BE)

11:35 DEPO1-O4-123 ● From temperature-independent to tunable resistivity of high-entropy alloys thin films
S-E. Benrazzouq, J. Ghanbaja, S. Migot, V. Milichko, J.F. Pierson
Univ. Lorraine, CNRS, IJL, Nancy (FR)

11:55 DEPO1-05-035 ● Reversible functionalization of citronellal plasma polymers - towards pH responsive thin films
J. Carneiro de Oliveira, P. Covin, A. Airoudj, F. Bally-Le Gall, V. Roucoules
Univ. Haute-Alsace, Univ. Strasbourg, CNRS, IS2M UMR 7361, Mulhouse (FR)

12:30 LUNCH

Tuesday 23 September

9:10 – 12:30

10:05 COFFEE BREAK

AMELI 1 – Plasma and/in liquid interaction ELLA FITZGERALD ROOM

Chair: M. Hori (JP)

10:35 AMELI1-O1-038 ● On the occurrence of internal partial discharges inside aluminium matrix composite layers during plasma electrolytic oxidation process
T. Czerwiec[1], A. Maizeray[1], G. Marcos[1], M.P. Planche[2], H. Liao[2], G. Henrion[1], J. Martin[1]
[1] Institut Jean Lamour, Univ. Lorraine - Nancy (FR)
[2] Univ. Marie et Louis Pasteur, UTBM, ICB - Montbéliard (FR)

10:55 AMELI1-O2-016 ● Investigation of the chemical behaviour of an electrolytic discharge used to synthesize low-density mesoporous metals
C. Boudat[1], F. Durut[1], R. Botrel[1], T. Belmonte[2]
[1] Commissariat à l'Energie et aux Energies Alternatives (CEA), Valduc, Is sur Tille (FR)
[2] Univ. Lorraine, CNRS, IJL, Nancy (FR)

11:15 AMELI1-O3-103 ● Degradation of methylene orange in aqueous solution using non-thermal plasma
T. Nguyen, G. Henrion, L. Sonhafouo Mbantio, T. Gries, C. Noël
Institute Jean Lamour - Equipe Plasmas - Procédés - Surfaces - Nancy (FR)

11:35 AMELI1-O4-102 ● Plasma technology for tetrodotoxin inactivation in *lagocephalus sceleratus* fishmeal
S. Mouchtouris[1, 2], G. Kokkoris[1, 2], M. Kotsiri[3], I. Kleidas[3], T.I. Anastasiou[3], E. Kagiampaki[3], M. Mandalakis[3], I. Nengas[3]
[1] School of Chemical Engineering, National Technical Univ. Athens - Athens (GR)
[2] Inst. Nanoscience & Nanotechnology, NCSR "Demokritos" - Athens (GR)
[3] Inst. Marine Biology, Biotechnology and Aquaculture, HCMR, Anavyssos & Heraklion (GR)

11:55 AMELI1-O5-112 ● Aerosol-assisted atmospheric pressure plasma deposition of active coatings based on natural antioxidant compounds
A. Lanza[1, 2], F. Palumbo[2], N. De Vietro[3], G. Mancini[3], A. Milella[1, 2], P. Favia[1, 2]
[1] Dpt. of Chemistry, Univ. Bari Aldo Moro - Bari (IT)
[2] CNR-NANOTEC, C/o Dpt. of Chemistry, Univ. Bari Aldo Moro - Bari (IT)
[3] Dpt. of Biosciences, Biotechnology and Environment, Univ. Bari Aldo Moro – Bari (IT)

12:30 LUNCH

Tuesday 23 September

14:00 – 15:45

ANTIPOLIS AUDITORIUM

Chair: L. Stafford (CA)

14:00 **PLENARY TALK //** On novel merits of (plasma-assisted) atomic layer deposition for next-generation energy applications
M. Creatore
Eindhoven Univ. of Technology – Eindhoven (NL)

GROM 1 Thin film growth and modelling

ANTIPOLIS AUDITORIUM

Chair: R. Clergereaux (FR)

14:45 GROM1-O1-022 ● The role of nitrogen additive on the growth of ultrathin silver films: in situ and real-time studies during magnetron sputtering deposition
D. Babonneau[1], G. Abadias[1], A. Michel[1], F. Pailloux[1], K. Solanki[1], A. Coati[2], Y. Garreau[2,3], A. Resta[2], A. Vlad[2], M. Kaminski[4], B. Krause[4]
[1] Institut Pprime - Poitiers (FR)
[2] SOLEIL synchrotron - Gif-sur-Yvette (FR)
[3] Laboratoire Matériaux et Phénomènes Quantiques - Paris (FR)
[4] KIT, Institute of Photon Science and Synchrotron Radiation - Karlsruhe (DE)

15:05 GROM1-O2-117 ● Improving TiO_2 anatase crystallization using a low power dielectric barrier discharge at atmospheric pressure in a single step process: a precursor and parametric study
N. Fosseur[1, 2], S. Godet[2], F. Reniers[1]
[1] Chemistry of Surfaces, Interfaces and Nanomaterials, Faculty of Sciences, Univ. Libre Bruxelles (BE)
[2] 4MAT, Engineering Faculty, Univ. Libre Bruxelles (BE)

15:25 GROM1-O1-130 ● Experimental and theoretical study of plasma polymerization into 3D structures
L. Zajickova[1,3], D. Necas[1], M. Janusova[1], L. Janu[1], P. De Navascues[2], D. Hegemann[2], N. Rusnakova[3]
[1] CEITEC - Brno (CZ)
[2] EMPA - St. Gallen (CH)
[3] Masaryk Univ. - Brno (CZ)

15:45 COFFEE BREAK

Tuesday 12 September

14:00 – 15:45

PSURF 1 Plasma surface processing

ELLA FITZGERALD ROOM

Chair: T. Tillocher (FR)

14:45 PSURF1-O1-075 ● Dry etch process development of gapless silicon nitride microlens array for CMOS imager sensors
A. Tavernier[1], F. Tomaso[1], R. Coquand[1], Z. Mehrez[1], C. Bellegarde[1], C. Sese[1], L. Masarotto[1], S. Guerroudj[2]
[1] Institut des Molécules et Matériaux du Mans, UMR 6283 CNRS, Univ. Le Mans (FR)
[2] ECAM RENNES − Louis de Broglie, Campus de Ker Lann, Bruz (FR)

15:05 PSURF1-O2-104 ● Development of plasma ALE for β-Ga_2O_3 using the gas mixture SF_6/Ar and CH_4/H_2
H. Beji, C. Cardinaud, A. Girard, C. Mannequin
Institut des Matériaux Jean Rouxel de Nantes - Nantes (FR)

15:25 PSURF1-O3-046 ● Plasma cryogenic processes applied to SiO_2 deep etching
R. Dussart[1], T. Tillocher[1], P. Lefaucheux[1], L. Becerra[1], L.J. Overzet[2]
[1] GREMI – Univ. Orléans - CNRS - Orléans (FR)
[2] PSAL - UT Dallas - Richardson (US)

15:45 COFFEE BREAK

Tuesday 12 September

16:15 – 17:20

GROM 2 Thin film growth and modelling

ANTIPOLIS AUDITORIUM

Chair: L. Zajickova (CZ)

16:15 **KEYNOTE //** GROM2-K1-045 ● Metal thin films growth by magnetron sputter deposition in He: numerical and experimental approach
A-L. Thomann[1], P. Brault[1], T. Sauvage[2], A. Fernandez[3], A. Caillard[1]
[1] GREMI (CNRS/Univ. Orléans) - Orléans (FR)
[2] CEMHTI CNRS - Orléans (FR)
[3] CSIC-Univ. Seville - Séville (ES)

16:45 GROM2-01-005 ● Influence of the nature of the transition metal in oblique angle deposition
A. Besnard, H. Gerami, N. Martin
Univ. Marie et Louis Pasteur, SUPMICROTECH, CNRS, Institut FEMTO-ST - Besançon (FR)

17:05 GROM2-02-108 ● Kinetic monte carlo simulation of hetero-epitaxial deposition of metal onto silicon substrate; influence of multistep deposition process
C. Mastail, A. Muriel Sanchez, P. Polisetty, A. Michel, G. Abadias
Institut Pprime - Poitiers (FR)

17:30 POSTER SESSION #1
& INDUSTRIAL EVENING

Tuesday 23 September

16:15 – 17:30

PSURF 2 Plasma surface processing ELLA FITZGERALD ROOM

Chair: M. Creatore (NL)

16:15 **KEYNOTE //** PSURF2-K1-090 ● Numerical simulations and ion beam experiments for the analyses of surface reactions for reactive ion etching
S. Hamaguchi
Univ. Osaka (JP)

16:45 PSURF2-O1-107 ● Enhancing plasma etching efficiency via physics-based modeling, experimental measurements, machine learning, and optimization algorithms
E. Boniakou[1], S. Mouchtouris[2], T. Boura[3], C. Zormpa[2], A. Kondi[2], D. Belounis[4], T. Giannakopoulos[3], A. Armaou[4], V. Constantoudis[2], E. Gogolides[2], G. Kokkoris[1]
[1] School of Chemical Engineering, National Technical Univ. of Athens - Athens (GR)
[2] Institute of Nanoscience & Nanotechnology, NCSR Demokritos - Athens (GR)
[3] Institute of Informatics & Telecommunications, NCSR Demokritos - Athens (GR)
[4] Chemical Engineering Department, Univ. Patras - Patras (GR)

17:05 PSURF-O2-049 ● Formation of black silicon microstructures by the stiger etching process for microfluidic applications
A. Rahali, A. Stolz, L. Becerra, P. Lefaucheux, R. Dussart, T. Tillocher
GREMI, Univ. Orléans, CNRS UMR 7344 - Orléans (FR)

17:30 POSTER SESSION #1
& INDUSTRIAL EVENING

Wednesday 24 September

8:40 – 10:05

ANTIPOLIS AUDITORIUM

Chair: S. Konstantinidis (BE)

8:40 **PLENARY TALK //** Plasma responses to tailored voltage waveforms in capacitively coupled plasmas
A. Lietz[1], S. Zulqarnain[1], N. Tabassum[1], B. Peete[1], J. Prager[2], T. Ziemba[2], P. Melnik[2], J. Perry[2], S. Shannon[2]
[1] North Carolina State Univ. - Raleigh (US)
[2] EHT Semi - Seattle (US)

DEPO 2 Plasma-assisted deposition, coatings and layers

ANTIPOLIS AUDITORIUM

Chair: C. Costin (RO)

9:25 DEPO2-O1-121 ● Erosion resistant PVD coatings on CFRP substrates
P. Abarca[1,3], T. Maerten[1], S. Belveze[1], S. Guimond[2], C. Jaoul[3], P. Tristant[3], M. Cavarroc[4]
[1] Oerlikon Balzers France (FR)
[2] Oerlikon Surface Solutions AG - Balzers (LI)
[3] Univ. Limoges (FR)
[4] Safran Tech - Paris (FR)

9:45 DEPO2-O2-067 ● Extraordinary oxidation behavior of W-Zr thin-film metallic glasses: a route for tailoring functional properties of W-Zr-O films
P. Zeman, M. Cervena, J. Houska, S. Haviar, J. Rezek, S. Zuzjakova
Department of Physics and NTIS - European Centre of Excellence, Univ. West Bohemia, Pilsen (CZ)

10:05 COFFEE BREAK

Wednesday 13 September

8:40 – 10:05

MODIDD 1 Modelling, diagnostics and data-driven optimization of plasma processes

ELLA FITZGERALD ROOM

Chair: S. Konstantinidis (BE)

9:25 MODIDD1-O1-070 ● Assisting plasma diagnostics with artificial intelligence methods: trends and applications in non-equilibrium plasmas operating from moderate-to-atmospheric pressures
D. Stefas[1], G. Makrypodi[2], K. Giotis[2, 1], L. Invernizzi[1], P. Svarnas[2], G. Lombardi[1], C. Lazzaroni[1], K. Gazeli[1]
[1] LSPM—CNRS & Univ. Sorbonne Paris Nord - Villetaneuse (FR)
[2] High Voltage Lab., Electrical & Computer Eng. Dept., Univ. Patras - Rion (GR)

9:45 MODIDD1-O2-019 ● µ-second pulse and RF coupling in an APPJ
A. Patelli[1], R. Fiorotto[1], E. Shakerinasab[1], T. Habib[2], B. Caillier[2]
[1] Univ. Padova (IT)
[2] Lab. DPHE, Univ. Toulouse, INU Champollion, Albi (FR)

10:05 COFFEE BREAK

Wednesday 24 September

10:35 – 12:30

DEPO 3 Plasma-assisted deposition, coatings and layers

ANTIPOLIS AUDITORIUM

Chair: M. Sankaran (US)

10:35 DEPO3-O1-047 ● Development and optimization of CrN coatings for enhanced tool performance in cryogenic machining of Ti_6Al_4V
G. Chettouh[1], S. Achache[1], L. Gueye[1], Y. Pinot[2], F. Sanchette[1], C. Nouveau[2], M. El Garah[1]
[1] LASMIS, Antenne de Nogent et LRC CEA-LASMIS, NICCI, Nogent (FR)
[2] Arts et Métiers Institute of Technology, LABOMAP, HESAM Univ., Cluny (FR)

10:55 DEPO3-O2-083 ● Enhanced morphology and ferroelectric properties of $Sc_{0.3}Al_{0.7}N$ sputterred thin films via a compositionally graded layers
T. Nguyen, D.T. Dao, M.S. Azeem, I. Nesterenko, M. Moridi, T. Xu
Silicon Austria Labs - Villach (AT)

11:15 DEPO3-O3-131 ● Control of the structure of tin sulfide thin films
J-F. Pierson, R. Juliac, D. Pilloud, S. Migot, A. Tahir, J. Ghanbaja, B. Vigolo, N. Stein
Univ. Lorraine, CNRS, IJL - Nancy (FR)

11:35 DEPO3-O4-115 ● Synthesis of metal doped diamond-like carbon films by magnetron sputtering
L. Marcinauskas[1, 2], H. Zhairabany[1], H. Khaksar[3], M. Milieška[2], A. Šarakovskis[4], E. Vanags[4]
[1] Department of Physics, Kaunas Univ. of Technology - Kaunas (LT)
[2] Plasma Processing Laboratory, Lithuanian Energy Institute - Kaunas (LT)
[3] Marian Smoluchowski Institute of Physics, Jagiellonian Univ. - Krakow (PL)
[4] Institute of Solid State Physics, Univ. Latvia - Riga (LV)

11:55 DEPO3-O5-057 ● The effect of ion potential energy on thin film crystallinity in pulsed filtered cathodic arc deposition
D. Kalanov[1], S. Mandazhiev[1], J. Franze[1], A. Anders[1, 2], Y. Unutulmazsoy[1]
[1] Leibniz Institute of Surface Engineering (IOM) - Leipzig (DE)
[2] Felix Bloch Institute of Solid State Physics, Leipzig Univ. - Leipzig (DE)

12:30 LUNCH

Wednesday 24 September

10:35 – 12:30

MODIDD 2 Modelling, diagnostics and data-driven optimization of plasma processes

ELLA FITZGERALD ROOM

Chair: A. Lietz (US)

10:35 MODIDD2-O1-024 ● Comparative analysis of ns- and ps-TALIF diagnostics of atomic oxygen generated with a plasma jet driven by a tailored voltage waveform
Y. Song[1], L. Invernizzi[2], D. Stefas[2], G. Lombardi[2], K. Gazeli[2], A. Nikiforov[1], A. Sobota[3], R. Morent[1]
[1] Research Unit Plasma Tech; Fac. of Engineering and Architecture, Univ. Ghent (BE)
[2] LSPM - CNRS, Univ. Sorbonne Paris Nord - Villetaneuse (FR)
[3] EPGD Group, Dpt. Applied Physics and Science Education, Univ. Eindhoven (NL)

10:55 MODIDD2-O2-093 ● Description of H-atom absolute densities and sub-ns decay times in a pulsed microtube plasma jet using ps-TALIF and a streak camera
Y. Agha, D. Stefas, L. Invernizzi, L. William, S. Prasanna, K. Gazeli, G. Lombardi
LSPM - CNRS, Univ. Sorbonne Paris Nord - Villetaneuse (FR)

11:15 MODIDD2-O3-082 ● Unraveling no production in N_2–O_2 plasmas with 0D kinetic modeling and experimental validation
T. Silva[1], S. Bera[2], C. Pintassilgo[1,3], A. Herrmann[2], S. Welzel[2], M. Tsampas[2], R. van de Sanden[2], V. Guerra[1]
[1] Inst. de Plasmas e Fusão Nuclear (IPFN), Inst. Superior Técnico, Univ. Lisboa (PT)
[2] Dutch Institute for Fundamental Energy Research (DIFFER) - Eindhoven (NL)
[3] Departamento de Engenharia Física, Faculdade de Engenharia, Univ. Porto (PT)

11:35 MODIDD2-O4-097 ● Time-resolved bayesian analysis of low-pressure misty plasmas using a collisional-radiative model coupled to optical emission spectroscopy
S. Chouteau[1], A. Durocher-Jean[2], M. Richard-Plouet[3], A. Granier[3], L. Stafford[2]
[1] Univ. Osaka (JP)
[2] Univ. Montréal, Québec (CA)
[3] Institut des Matériaux Jean Rouxel de Nantes (FR)

11:55 MODIDD2-O5-099 ● Transient behavior of charged particles in pulse-modulated inductively coupled Cl_2 discharge
S. Kim, J.P. Booth, G. Curley
Laboratoire de Physique des Plasmas - Palaiseau (FR)

12:30 LUNCH

Wednesday 24 September

14:00 – 16:05

ANTIPOLIS AUDITORIUM

Chair: T. Belmonte (FR)

14:00 **PLENARY TALK //** Fundamental diagnostics and modeling for streamer discharge and its application for cancer treatment
R. Ono
Univ. Tokyo (JP)

AMELI 2 Plasma and/in liquid interaction

ANTIPOLIS AUDITORIUM

Chair: T. Belmonte (FR)

14:45 AMELI2-O1-055 ● Reactive sputtering onto ionic liquid, a new process to synthesize compound nanoparticles
A. Bousquet[1], S. Ibrahim[1], V. Ntomprougkidis[1], J.M. Adanson[1], P. Bonnet[1], M. Richard-Plouet[2], M. Le Granvalet[2], S. Roth[3], A. Bonduelle[3]
[1] ICCF - Clermont-Ferrand (FR)
[2] IMN - Nantes (FR)
[3] IFPEN - Solaize (FR)

15:05 AMELI2-O2-058 ● Sputtering of silver onto silicone oils: nanoparticle formation and mass transfer into the bulk solution
F-E. Bol, S. Konstantinidis
UMons - ChIPS - Mons (BE)

15:25 AMELI2-O3-030 ● Formation of Ru catalytic nanoparticles onto polyethylene glycol by plasma sputtering
A. Diop[1], S. Atmane[1], L. Gimenez[1], J. Lemaire[1], E. Millon[1], S. Iseni[1], A. Saulduboi[1, 2], P. Andreazza[3], A. Caillard[1]
[1] GREMI – CNRS, Univ. Orléans (FR)
[2] MACLE – CNRS - Orléans (FR)
[3] ICMN – CNRS, Univ. Orléans (FR)

15:45 AMELI2-O4-080 ● Deposition of $ZnGa_2O_4$ thin films by reactive co-sputtering of liquid gallium
J. Purans, M. Zubkins, E. Strods, E. Butanovs
Institute of Solid State Physics, Univ. Latvia, Riga (LV)

16:05 COFFEE BREAK

16:35 POSTER SESSION #2 (UNTIL 18:30)

Wednesday 24 September

14:00 – 16:05

ITEC 1 Innovative applications, solutions and technologies

ELLA FITZGERALD ROOM

Chair: J. Alami (MA)

14:45 ITEC1-O1-048 ● Metal oxide reduction using inline openair-plasma process in combination with thin film deposition to enhance adhesion and improve durability in electronics
D. Bensalem, M. Buske, Y. Hamedi, S. Kulkarni
Plasmatreat, Steinhagen (DE)

15:05 ITEC1-O2-015 ● Pushing the limits of magnetron sputtering for innovative solutions
E. Haye[1], D. Muller[1, 2], C. Vandenabeele[1, 3], S. Lucas[1]
[1] ICS - Innovative Coating Solutions - Gembloux (BE)
[2] NCE, ULiège - Liège (BE)
[3] LARN-NISM, UNamur - Namur (BE)

15:25 ITEC1-O3-006 ● Unravelling the mechanisms behind dislocation density reduction in tungsten-doped single-crystal diamond: a synchrotron X-ray investigation
D. Nusimovici[1, 2], L. Valera[1], T.N. Tran-Caliste[3], J. Baruchel[3], O. Mathon[3], D. Eon[4], D. Chaussende[2], J. Bousquet[1]
[1] DIAMFAB, Grenoble (FR)
[2] Univ. Grenoble Alpes, CNRS, Grenoble INP, SIMaP, Grenoble (FR)
[3] ESRF, Grenoble (FR)
[4] Institut Néel, Grenoble (FR)

15:45 ITEC1-O4-139 ● Analysis and monitoring of protective coatings: advances in LECO's Glow Discharge Spectroscopy (GDS)
A. Houel[1], S. Bohm[2], V. Dubujet[1]
[1] LECO France (FR)
[2] LECO Europe (FR)

16:05 COFFEE BREAK

16:35 POSTER SESSION #2 (UNTIL 18:30)

Thursday 25 September

8:40 – 10:00

ANTIPOLIS AUDITORIUM

Chair: A. Granier (FR)

8:40 **PLENARY TALK //** Plasma technologies advancing biomedicine and sustainability
M. Bilek[1,2], C. Tran[1], A. Gilmour[2], S. Cottam[1], J. Sardharwalla[2], S. Fraser[2]
[1] School of Physics, Univ. Sydney (AU)
[2] School of Biomedical Engineering, Univ. Sydney (AU)

DEPO 4 Plasma-assisted deposition, coatings and layers ANTIPOLIS AUDITORIUM

Chair: A. Granier (FR)

9:25 DEPO4-O1-004 ● Plasma deposition in non-equilibrium conditions
D. Hegemann, P. Navascues
EMPA - St.Gallen (CH)

~~9~~:45 DEPO4-O2-040 ● Atmospheric-pressure Plasma Enhanced Chemical Vapor Deposition of size agents on glass fibers for glass-reinforced plastics
M. Troia[1], M. Haag[2], C. Dobslaw[3], D. Dobslaw[4], A. Schulz[1], M. Walker[1], D. Ben Salem[5], P. Holste[5], P. Delfs[5], A. Knospe[5], B. Glocker[3]
[1] IGVP, Univ. Stuttgart (DE)
[2] ITA RWTH Aachen Univ. (DE)
[3] PlasmaAir AG - Weil der Stadt (DE)
[4] TTI GmbH - Stuttgart (DE)
[5] PlasmaTreat GmbH - Steinhagen (DE)

10:05 COFFEE BREAK

Thursday 25 September

8:40 – 10:00

PSURF 3 Plasma surface processing

ELLA FITZGERALD ROOM

Chair: J-F. Pierson (FR)

9:25 PSURF3-O1-033 ● In-situ XRD investigations during nitriding of duplex steel
D. Manova[1], J. Bauer[1], A. Dalke[2, 3], S. Mändl[1]
[1] Leibniz Institute of Surface Engineering (IOM) - Leipzig (DE)
[2] Institute of Materials Engineering, Technische Univ. Bergakademie Freiberg - Freiberg (DE)
[3] ZeHS, Technische Univ. Bergakademie Freiberg - Freiberg (DE)

9:45 PSURF3-O2-029 ● Reduction of oxides using an Electron Cyclotron Wave Resonance Ar/H_2 plasma - towards H_2O production on the Moon
M. Sikiric[1,3], S. Bulou[2], K. Hadler[1,3], P. Choquet[3]
[1] European Space Resources Innovation Centre, LIST, Esch-sur-Alzette (LU)
[2] Advanced Plasma & Vapor Deposition Processes Engineering, LIST, Esch-sur-Alzette (LU)
[3] Univ. Luxembourg - Faculty of Science, Technology and Medicine - Esch-sur-Alzette (LU)

10:05 COFFEE BREAK

Thursday 25 September

10:35 – 12:30

DEPO 5 Plasma-assisted deposition, coatings and layers

ANTIPOLIS AUDITORIUM

Chair: M. Bilek (AU)

10:35 DEPO5-O1-092 ● Plasma polymer thin films as adhesion primers in composite/elastomer assembly: controlling adhesion performance through deposition parameters
M. Ezzehar, A. Airoudj, G. Schrodj, F. Bally-Le-Gall, V. Roucoules
Institut de Science des Matériaux de Mulhouse (IS2M), CNRS - Mulhouse (FR)

10:55 DEPO5-O2-109 ● Plasma polymer film as an interlayer to improve polymer-metal composites disassembly and recycling efficiency
A. Culot[1], R. Dantinne[1], S.A. Raut[1], D. Cossement[2], J.M. Raquez[3], D. Thiry[1]
[1] Chimie des Interactions Plasma-Surface (ChIPS), Univ. Mons (BE)
[2] Materia Nova Research Center, Parc Initialis, Mons (BE)
[3] Service des Matériaux Polymères et Composites (SMPC), Univ. Mons (BE)

11:15 DEPO5-O3-110 ● Study of the chemical and textural properties of 2-vinylpyridine-based plasma polymers
R. Costes[1,2], A. Van der Lee[1], S. Badaire[2], A. Achille[2], V. Rouessac[1], S. Roualdes[1]
[1] Institut Européen des Membranes (IEM) - Montpellier (France)
[2] Manufacture française des pneumatiques Michelin - Cébazat (France)

11:35 DEPO5-O4-020 ● Impact of surface chemistry on the morphology of plasma polymers
P. Covin[1], A. Airoudj[1], C. Noël[2], F. Bally-Le Gall[1], T. Belmonte[2], V. Roucoules[1], J. Carneiro De Oliveira[1]
[1] Univ. Haute-Alsace, Univ. Strasbourg, CNRS, IS2M UMR 7361 - Mulhouse (FR)
[2] Univ. Lorraine, CNRS, IJL - Nancy (FR)

11:55 DEPO5-O5-039 ● Formation of radicals in amine plasma polymer thin films and their potential for covalent binding of biomolecules
L. Janu[1], B. Beliančínová[1], V.T. Santana[2], P. Skládal[3], L. Zajíčková[1, 4]
[1] Plasma Technologies, CEITEC, Univ. Brno (CZ)
[2] Magneto-Optical and THz Spectroscopy, CEITEC, Univ. Brno (CZ)
[3] Dpt. of Biochemistry, Faculty of Science, Masaryk Univ., Brno (CZ)
[4] Dpt. of Condensed Matter Physics, Faculty of Science, Masaryk Univ., Brno (CZ)

12:30 LUNCH

Thursday 25 September

10:35 – 12:30

PSURF 4 Plasma surface processing

ELLA FITZGERALD ROOM

Chair: R. Dussart (FR)

10:35 PSURF4-O1-001 ● Transient signals measurement capability for the analysis of thin films and surfaces reactivity
P. Chapon, A. Stankova, L. Garrido
Horiba France - Palaiseau (FR)

10:55 PSURF4-O2-105 ● Plasma-surface characterization during V_2O_3 thin films etching in SF_6/Ar plasma
T. Mbouja Signe, C. Mannequin, A. Girard, C. Cardinaud
Institut des Matériaux de Nantes Jean Rouxel (IMN) - Nantes (FR)

11:15 PSURF4-O3-122 ● Sensing enhancement of chemiresistive gas sensors by surface functionalization
S. Kim
Inha Univ., Incheon (KR)

11:35 PSURF4-O4-111 ● Defect-engineered V_2O_5/TiO_2 thin films deposited by DC sputtering for improved carbofuran degradation
D. Pjević, J. Georgijević, T. Stamenković, T. Vulić
Institute of Nuclear Sciences "VINCA", Univ. Belgrade (RS)

11:55 PSURF4-O5-026 ● Cleaning process of 3D and delicate heterogeneous structures with HDRF®, optimize chemistry with remote plasma, for microelectronics' and medical applications
M. Segers, G. Terenziani, S. Benkoula
Plasma-Therm Europe - Grenoble (FR)

12:30 LUNCH

Thursday 25 September

14:00 – 15:45

ANTIPOLIS AUDITORIUM

Chair: M. Richard-Plouet (Fr)

14:00 **PLENARY TALK //** Tackling Lithium-ion battery challenges with PVD technologies
J. Alami
Mohammed VI Polytechnic Univ. (MA)

PSURF 5 Plasma surface processing

ANTIPOLIS AUDITORIUM

Chair: M. Richard-Plouet (FR)

14:45 PSURF5-O1-007 ● Enhancing corrosion resistance of magnesium alloys with plasma treatment and electrospun biodegradable polymer coatings
L. Zahedi, P. Ghourchi Beigi, M. Stupavská, D. Kovačik
Dpt. of Plasma Physics and Technology, CEPLANT, Faculty of Science, Masaryk Univ., Brno (CZ)

15:05 PSURF5-O2-114 ● Elucidating the growth mechanism of functionnalized plasma polymer films using complex geometry substrates at various substrate temperatures
R. Dantinne, P. Leclere, D. Thiry
Univ. Mons (UMons) (BE)

15:25 PSURF5-O3-124 ● Plasma-induced physicochemical and topographical surface modifications for enhanced polymer adhesion
J-F. Coulon[1, 2], D. Debarnot[2], M. Yengui[1], A. Al Khatib[1]
[1] ECAM Louis de Broglie - Rennes (FR)
[2] Institut des Molécules et Matériaux du Mans - Le Mans (FR)

15:45 COFFEE BREAK

Thursday 25 September

14:00 – 15:45

MODIDD 3 Modelling, diagnostics and data-driven optimization of plasma processes

ELLA FITZGERALD ROOM

Chair: C. Pintassilgo (PT)

14:45 MODIDD3-O1-113 ● Understanding backscattered ions in HiPIMS plasmas
Z. Belkaid, T. Minea, A. Revel
Laboratoire Physique des Gaz et Plasmas - Orsay (FR)

15:05 MODIDD3-O2-054 ● Enhancing energy flux to insulating surfaces using unipolar and bipolar HiPIMS pulse configurations
M. Farahani, T. Kozák, A. Dagmar Pajdarová, J. Čapek
Dpt. Physics & NTIS - European Centre of Excellence, Univ. West Bohemia, Pilsen (CZ)

15:25 MODIDD3-O3-037 ● Exploring ionized metal flux fraction in magnetron sputtering: insights from laboratory and industrial applications
P. Vasina[1], P. Klein[1], M. Ondryas[1], G. Lelovics[1], V. Sochora[2], M. Ucik[3], J. Kluson[3], M. Jilek[3], A. Lümkemann[4], J. Hnilica[1]
[1] Masaryk Univ. - Brno (CZ)
[2] SHM - Sumperk (CZ)
[3] Platit - Sumperk (CZ)
[4] Platit - Selsach (CH)

15:45 COFFEE BREAK

Thursday 25 September

16:15 – 18:05

DEPO 6 Plasma-assisted deposition, coatings and layers

ANTIPOLIS AUDITORIUM

Chair: V. Jousseaume (FR)

16:15 DEPO6-O1-042 ● Hexagonal Boron Nitride deposition using micro-Plasma Enhanced Chemical Vapour Deposition (µPECVD) based on a Micro Hollow Cathode Discharge (MHCD)
B. Menacer, K. Gazeli, C. Lazzaroni, V. Mille
CNRS LSPM - Villetaneuse (FR)

16:35 DEPO6-O2-116 ● Plasma-Enhanced Chemical Vapor Deposition of SiON optical thin films and nano-laminates
S. Calvez, P. Dubreuil, A. Monmayrant, O. Gauthier-Lafaye
LAAS-CNRS - Toulouse (FR)

16:55 DEPO6-O3-051 ● Packaging solutions with plasma technology for enhancing gases barrier properties
L. Coelho[1], J. Rodeigues[1], F. Loureiro[1], M. Marques[1], C. Ribeiro[2], N. Pereira[3], A. Rebola[3]
[1] CeNTI - Centre of Nanotechnology and Advanced Materials - Vila Nova de Famalicão (PT)
[2] TECMEAT - Agri-food Competence Center for the Meat sector - Vila Nova de Famalicão (PT)
[3] UR - United Resins S.A. - Figueira da Foz (PT)

17:15 DEPO6-O4-120 ● Atmospheric pressure plasma-assisted deposition of zinc-based coatings for agriculture applications
M. Roggio[1, 2], M. Zabihzadeh Khajavi[3, 4], A. Nikiforov[3], F. Palumbo[2], P. Favia[1], N. De Geyter[3]
[1] Univ. Bari Aldo Moro, Department of Chemistry - Bari (IT)
[2] Institute of Nanotechnology National Research Council (CNR-NANOTEC) - Bari (IT)
[3] Ghent Univ., Dpt. of Applied Physics, RUPT - Ghent (BE)
[4] Ghent Univ., Dpt. of Food Technology, Safety and Health, RUFMFP - Ghent (BE)

17:35 DEPO6-O5-061 ● TiO_xC_y organometallic multilayers for titanium dental implants: the role of carbon in promoting osseointegration
S. Rubio, L. Houssiau
Univ. Namur (BE)

19:30 CONFERENCE DINNER COCKTAIL (UNTIL 22:30)

Thursday 25 September

16:15 – 18:05

MODIDD 4 Modelling, diagnostics and data-driven optimization of plasma processes

ELLA FITZGERALD ROOM

Chair: T. Minea (FR)

16:15 MODIDD4-O1-021 ● Diagnostic of DC arc plasmas in aeronautic arc fault conditions: application to detection
A. Hellé, R. Hugon, F. Brochard, G. Marcos
Institut Jean Lamour - Nancy (FR)

16:35 MODIDD4-O2-088 ● Plasma processing of monolayer graphene explored with numerical simulations
P. Vinchon[1], N. Mauchamp[1], L. Spiske[1], Y. Miyamoto[2], C. Bock[3], S. Hamaguchi[1]
[1] Univ. Osaka (JP) - [2] National Institute of AIST, Tsukuba (JP)
[3] Ruhr-Univ. - Bochum (DE)

NANO 1 Plasma nanotechnologies

ELLA FITZGERALD ROOM

Chair: U. Cvelbar (SI)

16:55 NANO1-O1-028 ● DC plasma-inducted phase and morphological evolution of PtSn and PtRuSn nanoparticles produced in a magnetron-based gas aggregation source
A. Aryan[1,2], A. Caillard[1,3], M. Mikikian[1], P. Andreazza[2]
[1] GREMI, Univ. Orléans (FR) - [2] ICMN, Univ. Orléans (FR)
[3] UTOPII, AMU, CNAM, École Ponts ParisTec, INSA Lyon, Sorbonne Univ. (FR)

17:15 NANO1-O2-076 ● Thermally-induced microstructural evolution in nanoparticle-based CuO, WO_3 and CuO-WO_3 thin films for hydrogen gas sensing
J. Capek, K. Shaji, S. Haviar, P. Zeman, M. Procházka, R. Čerstvý, N. Kumar
Univ. West Bohemia, Pilsen (CZ)

17:35 NANO1-O3-086 ● Novel nanocomposite thin films by pulsed laser processes for plasmonic based sensing of cancer markers
M. Gireau[1], F. Du[2], J. Youssef[3,4], S. Vergnole[4], G. Humbert[3], S. Zeng[2], F. Dumas-Bouchiat[1], C. Champeaux[1]
[1] Univ. Limoges, CNRS, IRCER, UMR 7315, Limoges (FR)
[2] Univ. Troyes, CNRS, L2n, UMR 7076, Troyes (FR)
[3] Univ. Limoges, CNRS, XLIM, UMR 7252, Limoges (FR)
[4] ALPhANOV, Optics and Lasers Tech. Ctr., Inst. Optique d'Aquitaine - Limoges (FR)

17:55 NANO1-O4-052 ● Saturated plasmonic colours for identity security features obtained by magnetron sputtering and laser treatment
N. Jacquot[1], W. Ravisy[1], L. Dubost[1], C. Hubert[2], T. Girardin[2], R. Mermillod-Blondin[2], N. Destouches[2]
[1] IREIS, HEF Groupe, Andrézieux-Bouthéon (FR)
[2] Laboratoire Hubert Curien, Univ. Jean Monnet, Saint-Étienne (FR)

19:30 CONFERENCE DINNER COCKTAIL (UNTIL 22:30)

Friday 26 September

8:40 – 10:05

ANTIPOLIS AUDITORIUM

Chair: R. Snyders (BE)

8:40 **PLENARY TALK //** Plasma-catalyst interaction mechanisms for CO_2 recycling and molecule conversion
O. Guaitella[1], D. Sadi[1], S. Bravo[1], B. Berdugo[1], M. Budde[1], D. Pai[1], T. Silva[2], V. Guerra[2]
[1] LPP, CNRS, Sorbonne Univ., École Polytechnique, Institut Polytechnique de Paris, Palaiseau (FR)
[2] Instituto de Plasmas e Fusão Nuclear, Instituto Superior Técnico, Univ. Lisboa (PT)

ITEC 2 Innovative applications, solutions and technologies

ANTIPOLIS AUDITORIUM

Chair: T. Silva (PT)

9:25 ITEC2-O1-135 ● Enhancing CO_2 plasma conversion by in-situ oxygen removal using a Solid Oxide Electricochemical Cell (SOEC)
R. van de Sanden[1], G.J. Zhang[2], A. Pikalev[1], X. Chen[1]
[1] Dutch Institute of Fundemental Energy Research, Eindhoven (NL)
[2] School of Electrical Engineering, Xi'An Jiaotong Univ. - Xi'An (CN)

9:45 ITEC2-O2-034 ● Exploring the potential of a pulsed thermionic vacuum arc as metal ion propulsion system
C. Costin[1], V. Tiron[2], G. Andrisan[1], I.L. Velicu[1]
[1] Faculty of Physics, Alexandru Ioan Cuza Univ. Iasi - Iasi (RO)
[2] Research Centre on Advanced Materials and Technologies, Dpt. Exact and Natural Science, Institute of Interdisciplinary Research, Alexandru Ioan Cuza Univ. Iasi - Iasi (RO)

10:05 COFFEE BREAK

Friday 26 September

8:40 – 10:05

DEPO 7 Plasma-assisted deposition, coatings and layers

ELLA FITZGERALD ROOM

Chair: G. Henrion (FR)

9:25 DEPO7-O1-091 ● Direct injection of iron acetate solutions in a low pressure plasma to prepare Fe_2O_3/TiO_2 nanocomposite thin films
S. Hekking[1, 2], A. Goullet[1], A. Granier[1], C. Maheu[1], L. Stafford[2], M. Richard-Plouet[1]
[1] Nantes Univ., CNRS, Institut des Matériaux de Nantes Jean Rouxel, Nantes (FR)
[2] Département de Physique, Univ. Montréal (CA)

9:45 DEPO7-O2-106 ● Aerosol assisted atmospheric pressure plasma deposition of hybrid TiO_2-based photoactive nanocomposite coatings for water remediation
R. Del Sole[1], F. Palumbo[2], C. Lo Porto[3], R. Comparelli[3], M.L. Curri[1,3], F. Fracassi[1,2], A. Milella[1,2]
[1] Univ. Bari Aldo Moro, Department of Chemistry - Bari (IT)
[2] Istituto di Nanotecnologia, CNR - Bari (IT)
[3] Istituto per i Processi Chimico-Fisici, CNR - Bari (IT)

10:05 COFFEE BREAK

Friday 26 September

10:35 – 12:10

ITEC 3 Innovative applications, solutions and technologies

ANTIPOLIS AUDITORIUM

Chair: S. Hamaguchi (JP)

10:35 **KEYNOTE //** ITEC3-K1-125 ● Study of CH_4 pyrolysis in a planar atmospheric gliding arc discharge
R. Snyders
Univ. Mons (BE)

11:05 ITEC3-O1-044 ● Impact of swift heavy ions irradiation on the microstructural and electrochemical properties of sputtered vanadium nitride thin films for micro-supercapacitors
J. Barbé[1,2], A. Lebreton[1,2], C. Douard[1,2], C. Grygiel[3], I. Monnet[3], C. Lethien[4,2], T. Brousse[1,2]
[1] Nantes Univ., CNRS, Institut des Matériaux de Nantes Jean Rouxel, IMN, Nantes (FR)
[2] Réseau sur le Stockage Electrochimique de l'Energie (RS2E), CNRS FR 3459, Amiens (FR)
[3] CIMAP, Normandie Univ., CEA, CNRS, UNICAEN, Caen (FR)
[4] IEMN, Univ. Lille, CNRS, Univ. Polytechnique Hauts-de-France, UMR 8520 - IEMN, Lille (FR)

11:25 ITEC3-O2-084 ● Plasma thin films for high-frequency filtering supercapacitors
U. Cvelbar, N.M. Santhosh
Jožef Stefan Institute - Ljubljana (SI)

11:45 ITEC3-O3-078 ● Lanthanum niobium oxide thin films deposited via reactive sputtering for high power micro-batteries
O. Touré[1, 2], J. Barbe[1, 2, 3], M.P. Besland[1], T. Brousse[1, 2, 3]
[1] Institut des Matériaux de Nantes Jean Rouxel, CNRS - Nantes (FR)
[2] Nantes Univ. - Nantes (FR)
[3] Réseau sur le Stockage Electrochimique de l'Energie (RS2E) - Amiens (FR)

12:10 Closing ceremony ANTIPOLIS AUDITORIUM

14:00 SOCIAL PROGRAM

For registered person / 2 activities proposed:

- Option #1 - Excursion to Grasse, international capital of Flowers and Perfume
- Option #2 - Walking tour on the coastal path "sentier de Tire-Poil"

Friday 26 September

10:35 – 12:10

NANO 2 Plasma nanotechnologies

ELLA FITZGERALD ROOM

Chair: A. Bousquet (FR)

10:35 **KEYNOTE** // NANO2-K1-010 ● Optimisation and *in situ* control of the deposition of nanocomposite thin films in low pressure misty plasma
A. Granier[1], J. Chevet[1], M. Feron[2], R. Clergereaux[3], P. Raynaud[3], M. Kahn[2], A. Goullet[1], M. Richard-Plouet[1]
[1] Nantes Univ., CNRS, Institut des Matériaux de Nantes Jean Rouxel, Nantes (FR)
[2] Laboratoire de Chimie de Coordination UPR8241, CNRS, Toulouse (FR)
[3] Laplace, Univ. Toulouse, CNRS, UPS, INPT, Toulouse (FR)

11:05 NANO2-O1-069 ● Metal-doped DLC coating by PE-CVD coupled with pulsed liquid injection
H. Klein[1,2,3], L. Stafford[3], R. Clergereaux[2], M.L. Kahn[2]
[1] CNRS-LCC - Toulouse (FR)
[2] LAPLACE – Toulouse (FR)
[3] Univ. Montréal (CA)

11:25 NANO2-O2-041 ● Growth of gold-palladium nanoalloys by oblique angle deposition: exploration of their structure and optical properties
M. Costes, J. Ramade, S. Rousselet, K. Dussaillant, M. Marteau, F. Pailloux, S. Camelio, D. Babonneau
Institut Pprime, CNRS, Univ. Poitiers, ISAE-ENSMA - Poitiers (FR)

11:45 NANO2-O3-018 ● Oblique angle co-sputtering of nanostructured Ti-W thin films: influence of deposition current on structure and electrical properties
H. Gerami, A. Besnard, J.M. Cote, N. Martin
Femto-st institute - Besançon (FR)

12:10 Closing ceremony — ANTIPOLIS AUDITORIUM

14:00 SOCIAL PROGRAM

For registered person / 2 activities proposed:

- Option #1 - Excursion to Grasse, international capital of Flowers and Perfume
- Option #2 - Walking tour on the coastal path “sentier de Tire-Poil”

PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

POSTER PROGRAM

- **P1 / Session #1**
  with exhibition cocktail
  Tuesday 23 September
  17:30 - 19:30
    - AMELI
    - DEPO
    - ITEC
    - MODIDD

- **P2 / Session #2**
  with refreshments
  Wednesday 24 September
  16:35 - 18:30
    - DEPO
    - GROM
    - MODIDD
    - NANO
    - PSURF

Poster session #1

AMELI **Plasma and/in liquids interaction**

AMELI-P1-053 Slow pulsed sputtering onto liquid: importance of surface refreshment and of plasma heating
A. Caillard, S. Atmane, A. Diop, E. Millon, P. Brault
GREMI CNRS / Univ. Orléans (FR)

AMELI-P1-128 The influence of the discharge parameters on the physicochemical properties of plasma activated water
L. Marcinauskas[1], E. Jankaitytė[2], M. Aikas[1], L. Ragelienė[2], R. Uscila[1], A. Tamošiūnas[1], Z. Naučienė[2], V. Mildažienė[2]
[1] Plasma Processing Laboratory, Lithuanian Energy Institute - Kaunas (LT)
[2] Faculty of Natural Sciences, Vytautas Magnus Univ. - Kaunas (LT)

AMELI-P1-146 Exfoliation and functionalization of graphite particles by pulsed plasma discharges in the gas-liquid phase
A. Reguig, R. Chevigny, S. Cuynet, S. Fontana, C. Herold-Mareche, M. Ponçot, L. Adrien
Institut Jean Lamour, UMR 7198 CNRS – Univ. Lorraine - Nancy (FR)

AMELI-P1-147 Enhancement of grain quality of brewer's rice cultivar with plasma treatment of caryopsis using "Smart Agriculture System" based on collected data
M. Hori, H. Hashizume
Nagoya Univ. - Nagoya (JP)

AMELI-P1-154 Optimizing ammonia decomposition for enhanced hydrogen production in a novel rotating gliding arc reactor
M. Garcia Martinez[1], S. Marin-Meana[2], A. Megías-Sánchez[2], M. Ruiz-Martin[2], J. Cotrino[2], A. González-Elipe[2], M. Oliva-Ramírez[3], A. Gómez-Ramírez[3]
[1] Univ. Cordoba (ES)
[2] Instituto de Ciencia de Materiales de Sevilla (ES)
[3] Univ. Sevilla (ES)

AMELI-P1-160 Liquid flow control in a dual-frequency APPJ on water solutions
R. Fiorotto, E. Shakerinasab, M. Pierno, A. Patelli
Department of Physics and Astronomy "G. Galilei", Univ. Padova (IT)

AMELI-P1-170 Fixation of nitrogen in water with the use of a multiphase plasma reactor
S. Mouchtouris[1, 2], A. Boudouvis[1], E. Gogolides[2], G. Kokkoris[1]
[1] School of Chemical Engineering, National Technical Univ. Athens (GR)
[2] Inst. Nanoscience & Nanotechnology, National Ctre of Scientific Research "Demokritos" - Athens (GR)

Poster session #1

DEPO **Plasma-assisted deposition, coatings and layers**

DEPO-P1-013 Elaboration of 316L/Cu composite alloy using a hybrid PVD/SPS process
Y. Pinot[1], A. Besnard[2], M.R. Ardigo-Besnard[3], F. Bussiere[3]
[1] Arts et Métiers Institute of Technology, LaBoMaP - Cluny (FR)
[2] Univ. Marie et Louis Pasteur, SUPMICROTECH, CNRS, Institut FEMTO-ST - Besançon (FR)
[3] Laboratoire ICB, UMR 6303 CNRS, Univ. Bourgogne Europe - Dijon (FR)

DEPO-P1-027 Development and investigation of advanced coatings for high-temperature applications
I. Toumi[1], S. Achache[1], A. Al Hussein[1], B. Panicaud[2]
[1] ICD-LASMIS, UTT, UMR 6281, CNRS, Nogent (FR)
[2] ICD-LASMIS, UTT, UMR 6281, CNRS, Troyes (FR)

DEPO-P1-050 Deposition of dielectric, and metal layer solution for TSV integration, innovative sequential process, application of low temperature deposition
M. Segers, P.D. Szkutnik, S. Benkoula
Plasma-Therm Europe - Grenoble (FR)

DEPO-P1-068 Development of hydrogen barrier thin films based on silicon carbonitride
M. Tetouani[1], A. Al Hussein[1], S. Achache[1], M. Cherkaoui[2]
[1] UR LASMIS, Univ. Technologie de Troyes - Nogent (FR)
[2] Univ. Ibn Tofaïl - Kenitra (MA)

DEPO-P1-072 Study of the impact of different dielectric materials on the performance and optical features of a Micro-Hollow Cathode Discharge (MHCD)
N. Chazapis, B. Menacer, D. Stefas, G. Lombardi, C. Lazzaroni, K. Gazeli
LSPM - CNRS & Univ. Sorbonne Paris Nord, Villetaneuse, Paris (FR)

DEPO-P1-140 On thermal stability and oxidation behavior of metastable W–Zr thin-film alloys
M. Červená, J. Houška, R. Čerstvý, P. Zeman
Department of Physics and NTIS - European Centre of Excellence, Univ. West Bohemia, Pilsen (CZ)

DEPO-P1-148 Influence of substrate bias on the properties and conformality of TiN thin films deposited by High Power Impulse Magnetron Sputtering (HiPIMS)
L. Seigneur[1], J. Barbé[1, 2], M.P. Besland[1]
[1] Nantes Univ., CNRS, Institut des Matériaux de Nantes Jean Rouxel, Nantes (FR)
[2] Réseau sur le Stockage Electrochimique de l'Energie (RS2E), CNRS FR 3459, Amiens (FR)

Poster session #1

DEPO-P1-149 Plasma-grown vertically oriented graphene for supercapacitor electrodes
A. Vesel, R. Zaplotnik, G. Primc
Jozef Stefan Institute - Ljubljana (SI)

DEPO-P1-158 Utilizing gas rarefaction to optimize preferential metal ion acceleration for epitaxial AlN growth on Silicon(111)
N. Behravan[1], T. Pitonakova[2], T. Terzic[3], A. Farhadizadeh[1], M. Deluca[4], M. Moridi[4], D. Solonenko[4], D. Lundin[1]
[1] Linköping Univ. - Linköping (SE)
[2] Masaryk Univ. - Brno (CZ)
[3] Otto-von-Guericke-Univ. Magdeburg - Magdeburg (DE)
[4] Silicon Austria Labs GmbH - Villach (AT)

DEPO-P1-161 Aerosols as an innovating route for thin film deposition by PECVD
R. Clergereaux[1], P.A. Goutal[1, 2, 3], M. Feron[1, 4], P. Raynaud[1], V. Rouessac[2], S. Roualdes[2], S. Devautour-Vinot[3], M.L. Kahn[4], J. Chevet[5], A. Goullet[5], A. Granier[5], M. Richard-Plouet[5]
[1] Laplace - Toulouse (FR)
[2] IEM - Montpellier (FR)
[3] ICGM - Montpellier (FR)
[4] LCC - Toulouse (FR)
[5] IMN - Nantes (FR)

DEPO-P1-162 Cu-substitution in lanthanum-deficient $LaFeO_3$ perovskites for enhanced photoelectrochemical solar hydrogen production
T. Gries[1], V. Guigoz[1, 2], S. Migot[1], S. Bruyère[1], R. Schneider[2]
[1] Univ. Lorraine, CNRS, IJL - Nancy (FR)
[2] Univ.Lorraine, CNRS, LRGP - Nancy (FR)

DEPO-P1-164 Deposition and characterisation of nitride thin films for data-driven optimisation of oxidation resistance
L. Mereaux[1], C. Jaoul[1], E. Menou[2], T. Vaubois[2], M. Cavarroc[2]
[1] IRCER - Limoges (FR)
[2] Safran Tech - Magny-Les-Hameaux (FR)

DEPO-P1-168 Fe:CH thin film deposition using an iron acetate solution in a Dielectric Barrier Discharge
S. Hekking[1, 2], A. Goullet[2], A. Granier[2], C. Maheu[2], M. Richard-Plouet[2], L. Stafford[1]
[1] Département de Physique, Univ. Montréal (CA)
[2] Nantes Univ., CNRS, Institut des Matériaux de Nantes Jean Rouxel (IMN) - Nantes (FR)

Poster session #1

ITEC **Innovative applications, solutions and technologies**

ITEC-P1-062 Functionalized amorphous carbon coatings for low secondary electron yield and controlled surface resistance in particle accelerators
W. Vollenberg[1], P. Costa Pinto[1], L. Mourier[1], Y. Rabetsimialona[1], N. Bundaleski[2], I.M. Marrucho Ferreira[2], J. Deuermeier[2]
[1] CERN - Genève (CH)
[2] Univ. Nova de Lisboa - Lisbon (PT)

ITEC-P1-064 A low-temperature synthesis of strongly thermochromic VO_2-based coatings for energy-saving smart windows
M. Kaufman, E. M. Nia, J. Vlcek
Department of Physics and NTIS - European Centre of Excellence, Univ. West Bohemia, Pilsen (CZ)

ITEC-P1-085 Magnetron deposition of chromogenic thin films for smart windows
J. Purans, M. Zubkins
Institute of Solid State Physics, Univ. Latvia - Riga (LT)

ITEC-P1-129 Transforming leak detection in vacuum environment with remote plasma optical emission spectroscopy
B. Daniel, D. Monaghan
Gencoa Ltd - Liverpool (UK)

ITEC-P1-171 New QCM-Based diagnostic for quantitative time-resolved measurement of the ion flux in HiPIMS
C. Ballage[1], A. Kapran[2], O. Vasilovici[1], A. Bennacef[3], T. Minea[4]
[1] CNRS - LPGP - Orsay (FR)
[2] CNRS - LPGP / FZU - Orsay (FR)
[3] CNRS - LPGP / Sorbonne Univ. - Paris (FR)
[4] Univ. Paris-Saclay - LPGP - Orsay (FR)

MODIDD **Modelling, diagnostics and data-driven optimization of plasma processes**

MODIDD-P1-036 Open-source modeling of gas phase dynamics in industrial magnetron sputtering processes
J. Beyer, P. Nizenkov, S. Copplestone, A. Mirza
boltzplatz - numerical plasma dynamics GmbH - Stuttgart (DE)

MODIDD-P1-073 Rotational temperature measurements of N_2(C), NO(A), and OH(A) in different micro hollow cathode discharge configurations using Optical Emission Spectroscopy
D. Stefas[1], G. Makrypodi[2], B. Menacer[1], P. Svarnas[2], G. Lombardi[1], C. Lazzaroni[1], K. Gazeli[1]
[1] LSPM - CNRS & Univ. Sorbonne Paris Nord - Villetaneuse (FR)
[2] High Voltage Lab., Elec. & Computer Eng. Dpt., Univ. Patras, Rion (GR)

Poster session #1

MODIDD-P1-081 Assessing actinometry and line ratio techniques for species densities and electric field determination in DC glow discharges
T. Silva[1], L. Kuijpers[2], E. Baratte[3], V. Guerra[1], R. Van De Sanden[2], J.P. Booth[3], O. Guaitella[3]
[1] Institute for Plasmas and Nuclear Fusion (IPFN) - Lisbon (PT)
[2] Dutch Inst. for Fundamental Energy Research (DIFFER), Eindhoven (NL)
[3] Laboratoire de Physique des Plasmas (LPP) - Paris (FR)

MODIDD-P1-094 Two dimensional distribution of atomic nitrogen absolute density in three DC MHCD
K. Gazeli[1], A. Remigy[1], B. Menacer[1], K. Kourtzanidis[2], O. Gazeli[3], G. Lombardi[1], C. Lazzaroni[1]
[1] Univ. Sorbonne Paris Nord, LSPM, CNRS, UPR 3407 - Villetaneuse (FR)
[2] CPERI, (CERTH, Thermi (GR)
[3] FOSS Research Ctre for Sustainable Energy, Univ.Cyprus, Nicosia (CY)

MODIDD-P1-095 Analysis of sputtered species transport in High Power Impulse Magnetron Sputtering (HiPIMS) discharge employing magnetized QCM probe
A. Kapran[1], C. Ballage[1], Z. Hubička[2], T. Minea[1]
[1] LPGP, CNRS - Univ. Paris-Saclay - Orsay (FR)
[2] FZU – Inst. of Physics of the Czech Academy of Sciences - Prague (CZ)

MODIDD-P1-101 Plasma-surface interactions in CO_2 glow discharges
V. Guerra[1], B. Berdugo[2], A. Filipe[1], O. Guaitella[2], A.S. Morillo Candás[2], P. Viegas[1]
[1] Instituto de Plasmas e Fusão Nuclear, Instituto Superior Técnico, Univ. Lisboa (PT)
[2] LPP, CNRS, Sorbonne Univ., École Polytechnique, Institut Polytechnique de Paris - Palaiseau (FR)

MODIDD-P1-153 Study of the plasma pyrolysis of methane in a rotating gliding arc for carbon black synthesis
N. Roy[1], A. Panepinto[2], T. Godfroid[2], F. Mazeri[2], A. Usoltseva[3], V. Smits[3], R. Snyders[1, 2]
[1] Plasma-Surface Interaction Chemistry (ChIPS), Univ. Mons (BE)
[2] Materia Nova Research Center, Mons (BE)
[3] Innovation Centre, Phillips Carbon Black Limited, Ghislenghien (BE)

MODIDD-P1-157 Time-resolved measurements of secondary electron emission during ion bombardment
S. Mändl[1], H. Kersten[2], D. Manova[1]
[1] Leibniz Institute of Surface Engineering (IOM) - Leipzig (DE)
[2] Institut für Experimentelle und Angewandte Physik, Christian-Albrechts-Universität Kiel - Kiel (DE)

MODIDD-P1-167 Developing a modeling framework for plasma assisted solvolysis of fiber reinforced polymers
G. Kokkoris[1], A. Mouzakis[1], D. Passaras[1], D. Marinis[2], E. Farsari[2], S. Sfikas[2], E. Amanatides[2]
[1] School of Chemical Engineering, National Technical Univ. Athens (GR)
[2] Department of Chemical Engineering, Univ. Patras - Patras (GR)

Poster session #2

DEPO **Plasma-assisted deposition, coatings and layers**

DEPO-P2-002 Influencing the properties of TiN and (Ti,Al)N hard coatings by modifying their composition and structural design

D. Munteanu[1], C. Lopes[2], I. Borsan[1], C. Gabor[1], M.S. Rodrigues[2], A. Ferreira[2], F. Macedo[2], E. Alves[3], N.P. Barradas[3], F. Vaz[2]
[1] Dept. of Material Science, Transilvania Univ. Brasov - Brasov (RO)
[2] Physics Centre of Minho and Porto Univ. (CF-UM-UP), Univ. Minho - Braga (PT)
[3] IPFN, Instituto de Plasmas e Fusão Nuclear, Instituto Superior Técnico, Univ. Lisboa - Lisbon (PT)

DEPO-P2-011 HEA thin films as protective barrier against carbon diffusion during SPS

A. Besnard[1], M. El Garah[2], F. Sanchette[2], Y. Pinot[3], R. Charvet[4], M.R. Ardigo-Besnard[4], F. Herbst[4], N. Geoffroy[4]
[1] Univ. Marie et Louis Pasteur, SUPMICROTECH, CNRS, Institut FEMTO-ST - Besançon (FR)
[2] LASMIS, Antenne de Nogent et LRC CEA-LASMIS, NICCI, Nogent (FR)
[3] Arts et Métiers Institute of Technology, LaBoMaP - Cluny (FR)
[4] Laboratoire ICB, UMR 6303 CNRS, Univ. Bourgogne Europe - Dijon (FR)

DEPO-P2-014 Thermodynamic modeling and experimental investigation of Ti PVD coatings as protective barriers against carbon diffusion during SPS

Y. Pinot[1], R. Charvet[2], M.R. Ardigo-Besnard[2], F. Baras[2], S. Le Gallet[2], F. Herbst[2], N. Geoffroy[2], A. Besnard[3]
[1] Arts et Métiers Institute of Technology, LaBoMaP - Cluny (FR)
[2] Laboratoire ICB, UMR 6303 CNRS, Univ. Bourgogne Europe - Dijon (FR)
[3] Univ. Marie et Louis Pasteur, SUPMICROTECH, CNRS, Institut FEMTO-ST - Besançon (FR)

DEPO-P2-066 Nanostructuring of bismuth oxyfluoride thin films by oblique angle deposition for CO_2 photoconversion

A.E. Kabouia[1], A. Bousquet[1], S. Roth[2], A. Bonduelle[2], M. Richard-Plouet[3], M. Le Granvalet[3], R. Smaali[4], E. Centeno[4]
[1] Univ. Clermont Auvergne (UCA), ICCF - Clermont-Ferrand (FR)
[2] IFP Energies nouvelles - Solaize (FR)
[3] Nantes Univ., CNRS, Institut des Matériaux de Nantes Jean Rouxel (FR)
[4] Univ. Clermont Auvergne, Clermont Auvergne INP, CNRS, Institut Pascal - Clermont-Ferrand (FR)

Poster session #2

DEPO-P2-134 Discriminating between morphological and chemical effects on the antibacterial properties of metal thin films through laser surface structuring
A-L. Thomann[1], P. Birnal[1], F. Brule-Morabito[2], B. Aspe[1], N. Semmar[1], P. Andreazza[3], E. Bourhis[3], P. Brault[1], M. Cavarroc[4], A. Saulddubois[1], T. Vaubois[4], E. Menou[4], A. Caillard[1], C. Andreazza[3]
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[3] ICMN (CNRS / Univ. Orléans) - Orléans (FR)
[4] Safran Paris-Saclay – Safran Tech - Magny-les-Hameaux (FR)

DEPO-P2-142 Nanostructure engineering and properties enhancement of Cu-based films by Zr and Ta alloying
M. Zhadko, A. Benediktová, J. Houška, R. Čerstvý, P. Baroch, P. Zeman
Univ. West Bohemia - Pilsen (CZ)

DEPO-P2-151 Atomic Layer Deposition of ZnO on fullerene: comparing thermal and plasma-enhanced approaches towards a photoactive nanocomposite
R. Del Sole[1, 2], A. Milella[1, 2], F. Fracassi[1, 2], P. Parlanti[3], M. Gemmi[3], A.M. Coclite[4, 5], F. Palumbo[2]
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[2] CNR-Institute of Nanotechnology - Bari (IT)
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DEPO-P2-159 Recyclable thin coatings deposited by mean of plasma-assisted techniques on polymer foils for food packaging applications
F. Delfin[1,2], C. Forsich[1], M. Schachinger[1], S. Augl[1], S. Brühl[2], C. Burgstaller[1], D. Heim[1]
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[2] Univ. Tecnológica Nacional, Facultad Regional Concepción del Uruguay - Concepción del Uruguay (AR)

DEPO-P2-163 A new solution to remove macro-particles during reactive metal nitride arc Physical Vapour Deposition
D. Monaghan[1], P. Mccarthy[1], V. Bellido[1], T. Sgrilli[1], C. Bamber[2]
[1] Gencoa - Liverpool (UK)
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Poster session #2

DEPO-P2-173 Plasma deposition of III-V semiconductors: sputtering and RPVPE approaches
K. Ouaras[1], P. Roca I Cabarrocas[1, 2], L. Watrin[1, 2], L. Srinivasan[1, 2], A. Eurosi[1, 2], D. Meurice[1]
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[2] Institut Photovoltaïque d'Ile-de-France (IPVF), Palaiseau (FR)

GROM Thin films growth and modelling

GROM-P2-043 Influence of discharge parameters on the properties of TiO_2 films grown by reactive Bipolar HiPIMS discharges
S. Debnarova[1], M. Michiels[1,2], S. Konstantinidis[1]
[1] Plasma-Surface Interaction Chemistry, Univ. Mons, Mons (BE)
[2] Haute École en Heinaut, Mons (BE)

GROM-P2-127 Multisource deposition conditions prediction towards required composition of thin films
J. Gutwirth[1], T. Halenkovič[1], S. Šlang[1], V. Nazabal[2, 1], P. Němec[1]
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[2] Univ. Rennes - Rennes (FR)

MODIDD Modelling, diagnostics and data-driven optimization of plasma processes

MODIDD-P2-009 Pure ammonia microwave discharges: a global model
T. Belmonte[1], M.Y. Awaji[1,2], L. Pentecoste[1], C. Noel[1], M. Belmahi[1], T. Gries[1]
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MODIDD-P2-017 Rate coefficients of the N + H + M(Ar, N_2) → NH + M recombination reaction in flowing afterglows of microwave plasmas
A. Ricard, V. Ferrer, J.P. Gardou, F. Marchal, J.P. Sarrette
LAPLACE, Univ. Toulouse, CNRS, UPS, INPT, Toulouse (FR)

MODIDD-P2-059 Experimental investigations on the impact of gas flow on the propagation dynamics of a pulsed-driven µm-scale plasma jet
Y. Agha[1], K. Giotis[1, 2], D. Stefas[1], L. Invernizzi[1], H. Hoeft[3], P. Svarnas[2], K. Gazeli[1], G. Lombardi[1]
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[2] Univ. Patras, Electrical & Computer Engineering Dept., High Voltage Lab., Rion - Patras (GR)
[3] Leibniz Inst. for Plasma Science and Technology (INP), Greifswald (DE)

Poster session #2

MODIDD-P2-098 Modelling N_2-H_2 for ammonia production
C. Pintassilgo[1, 2], S. Baghel[1], M. Budde[3], A. Gonçalves[1], O. Guaitella[3], L. Marques[4], P. Pereira[1], N. Pinhão[1], L.L. Alves[1]
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MODIDD-P2-100 Ion energy distribution function measurement in hybrid HiPIMS with carbon target
I. Naiko[1, 2], M. Čada[1], A. Ostapenko[1], Z. Hubička[1]
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MODIDD-P2-126 Optimizing ECR plasma ashing for high yield during spintronic sensor fabrication on 200mm wafers
F. Favita[1], S. Cardoso[1,2]
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[2] Instituto Superior Técnico (IST) - LIsbon (PT)

MODIDD-P2-137 Enhancing surface emission in micro-gap atmospheric discharge via harmonic excitation
Y. Liu[1], N. Le Thomas[2,3], C. Leys[1], A. Nikiforov[1]
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MODIDD-P2-156 Spectroscopy study of the LTE condition in the Laser Induced Breakdown used for the chlorine ion determination in building materials
M. Garcia Martinez, J. Mateo Calvo, A. Rodero Serrano
Univ. Cordoba (ES)

MODIDD-P2-165 TIA plasma characterization by optical emission spectroscopy in the presence of a substrate
B. Ganleu Monte[1], C. Chazelas[1], C. Dublanche-Tixier[1], P. Tristant[1], T. Belmonte[2]
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Poster session #2

MODIDD-P2-172 Line-specific radiation transport simulation in spatially non-uniform argon plasmas for self-consistent collisional-radiative modeling
S. Chouteau[1], H.C. Tsai[2], Z. Donko[3], T.V. Tsankov[4], P. Hartmann[3], J.S. Wu[2], S. Hamaguchi[5]
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NANO Plasma nanotechnologies

NANO-P2-012 Photoluminescent ZnO-SiO_2 nanocomposites prepared by a hybrid process coupling aerosol and Plasma Enhanced Chemical Vapour Deposition
M. Richard-Plouet[1], J. Chevet[1], M. Feron[2,3], A. Granier[1], M. Kahn[3], R. Clergereaux[2], A. Goullet[1]
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NANO-P2-087 Pulsed laser sources for nanometer-scaled complex materials and devices
M. Gireau[1], F. Du[2], J. Youssef[3, 4], S. Vergnole[4], G. Humbert[3], S. Zeng[2], C. Champeaux[1], F. Dumas-Bouchiat[1]
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PSURF Plasma surface processing

PSURF-P2-032 Stability of expanded austenite during annealing in vacuum
S. Mändl, D. Manova
Leibniz Institute of Surface Engineering (IOM) - Leipzig (DE)

PSURF-P2-074 Atomic Layer Etching of SiO_2 using CF_4 plasma in deposition regime at cryogenic temperature
T. Tillocher[1], M. Adjabi[1], J. Nos[1], S. Iseni[1], G. Cunge[2], M. Kogelschatz[2], P. Lefaucheux[1], L. Becerra[1], E. Despiau-Pujo[2], R. Dussart[1]
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Poster session #2

PSURF-P2-079 Novel atmospheric-pressure plasma curing of anti-corrosion transparent silicon-based coating
P. Ghourchi Beigi, L. Zahedi, R. Krumpolec, D. Kováčik
Dpt. Plasma Physics and Technology, CEPLANT, Faculty of Science, Masaryk Univ. - Brno (CZ)

PSURF-P2-133 Enhancing fiber/matrix interface in bio-based composites by cold plasma treatment: a step towards better fluid sealing
F. Perrier-Michon[1], S.A.E. Boyer[2], A. Burr[2], V. Rohani[1]
[1] PERSEE (MINES Paris PSL) - Sophia Antipolis (FR)
[2] CEMEF CNRS 7635 (MINES Paris PSL) - Sophia Antipolis (FR)

PSURF-P2-144 Regulation of peripheral plasma characteristics via engineered alterations in electrode shielding materials under a direct current-biased power configuration
C. Park[1, 2], J. Cho[3], G. Woo[4]
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PSURF-P2-150 Optimizing active screen plasma nitriding of AISI 316L through alternative approaches: reactor conditioning and argon addition
A. Adami Vidal, R. Hugon, C. Noël, T. Czerwiec, G. Marcos
Univ. Lorraine, CNRS, Institut Jean Lamour - Nancy (FR)

PSURF-P2-166 Performance optimization of metallic bipolar plates for PEMFCs by post-discharge plasma
L. Jacob[1, 2], G. Marcos[1], T. Gries[1], M. Hautier[2], T. Czerwiec[1]
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[2] Symbio - Saint-Fons (FR)

PSURF-P2-169 Comparison between filamentary and diffuse dielectric barrier discharges at atmospheric pressure for the treatment of monolayer graphene films
L. Stafford[1], C. Moderie[1], N. Naudé[2], R. Martel[1]
[1] Univ. Montréal (CA)
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EXHIBITORS

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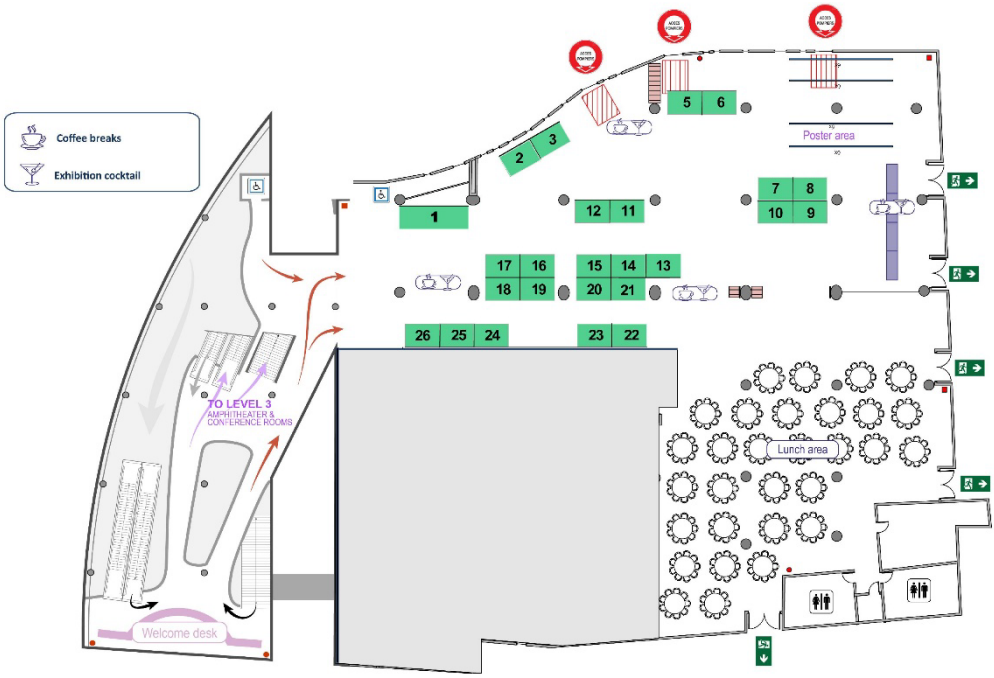

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Stand # 26

The Polytec group has a worldwide presence through its subsidiaries and representatives. As a manufacturer and specialist, Polytec designs optical measurement equipment for real-time non-destructive testing: vibrometry, velocimetry, surface metrology and on-line spectrometry.
Also a distributor, Polytec offers complementary product ranges in photonics, vision, industrial process, etc.
Polytec France supports all professionals in the public sector (Education, Research) and industry (Aeronautics, Automotive, Defence, Electronics, Food, Biomedical, Agriculture, Cosmetics, etc.).
Based in Chatillon (92), the French subsidiary operates throughout France and offers its customers a wide range of alternatives in addition to a high-quality technical and after-sales service: sales, rental, measurement services, training, etc.

Technosud II – Bât. A
99 rue Pierre Semard
92320 Chatillon (France)
+33 (0)1 49 65 69 00
info@polytec.fr
www.polytec.fr

PRO-VIDE

Stand # 13

Pro-Vide – Customized Solutions for Vacuum and Ultra-High Vacuum
Pro-Vide is a French designer and manufacturer with more than 50 years of expertise. We support our clients from needs analysis through to after-sales service, with a strong focus on performance and reliability.
With our design office, we create original technical solutions for vacuum and ultra-high vacuum environments. Our machining and metalworking workshop allows us to produce in-house:
- Vacuum chambers, components, viewports, ceramic/metal feedthroughs,
- Sample holders, manipulators, deposition sources, plasma systems, ovens…
Our experienced teams also provide a complete range of services:
- Maintenance, troubleshooting, machining of hard materials (ceramics, glass, sapphire),
- 5-axis waterjet cutting, stainless steel fabrication, laser/TIG welding…
In addition, we are an authorized distributor of vacuum equipment (pumps, cryogenerators, oils, RF/DC generators, gauges, fittings, etc.).
We are also official partners of **Kashiyama** and **Shimadzu**, renowned for their reliable and high-performance vacuum pumps.

24bis route de Fougères
41120 Cormeray (France)
+33 (0)2 55 99 65 05
contact@pro-vide.eu
www.pro-vide.eu

ROBEKO

Stand # 19

robeko is a supplier of components and materials as well as a technology partner for sputter deposition. We are European distributor for the cutting-edge products of our partners Sputtering Components, Ionautics, House of Plasma, Sairem, ICS, RF Industries, PLASUS, Magpuls and TFC GmbH. robeko provides planar and rotatable sputtering targets and bonding services for tribological, decorative and optical applications. We are proud of our in house manufacturing capabilities for cast planar targets and planar target bonding. As a technology partner our capabilities are ranging from feasibility studies and layer development to upscaling and process transfer into industrial production.

An der Heide 3 B
67678 Mehlingen (Germany)
+49 6303 999 67-00
info@robeko.de
www.robeko.de

SAIREM

Stand # 10

For more than 45 years, SAIREM has been designing innovative solutions for industry using microwave and RF technology: generators, high-performance industrial machines, and related services. The company offers one of the most advanced ranges for thermal processing and plasma generation.
SAIREM has developed a **patented solution combining solid-state microwave generators and advanced plasma sources**, capable of producing very high-density plasmas. These systems support a wide range of cutting-edge applications, including diamond synthesis by chemical vapor deposition (CVD), etching, PE-CVD, PE-ALD, and PE-ALE.
Among these innovations, the **PlasmaVac source** features a self-matching architecture that prevents power loss and enables matching across a wide range of operating conditions—without requiring an external impedance matching system. The second, a collisional-type source, enables processes requiring a high concentration of reactive species, such as high-rate PECVD or isotropic etching, with stable operation at pressures ranging from 1 to several tens of pascals.
SAIREM's **2540 MHz solid-state generators** deliver stable and precise microwave power, with continuous wave and pulsed modes. Their design ensures a long service life, excellent frequency stability, and safe operation without high voltage—making them particularly suitable for demanding plasma processes where reliability and fine control are essential.
Through its portfolio of patented technologies and commitment to innovation, SAIREM continues to lead the way in industrial microwave and plasma processing.

82 rue Elisée Reclus
69150 Décines-Charpieu (France)
+33 (0)4 72 01 81 60
commercial@sairem.com
www.sairem.com

SCIENTEC - PREVAC

Stand # 8

ScienTec is one of the largest distributors within the French market, specializing in the distribution of surface analysis technologies that span from nanometer to millimeter scales, catering to both research and industrial sectors.
ScienTec is the representative of Prevac that manufacture Vacuum systems for analysis & deposition (PVD-PLD-MBE).
Furthermore, ScienTec presents a wide-ranging selection of scientific equipment options, including:
- AFM microscopes: Best price / performance AFM (High resolution, ResiScope, HD-KFM, sMIM, multiple environments)
- SEM microscopes: Superior price-to-performance tabletop and standard SEM (robustness, ease-of-use, EDS analysis)
- IR and RAMAN spectroscopies: submicron scale, better than ATR
- Nanoindentors: Hardness, scratch, Young modulus, ambient/vacuum environments
- Optical and mechanical profilometers: single & automated measurements
- Vacuum systems for analysis & deposition (PVD – PLD – MBE)
- Thin film analyzers: Single-spot, microscopic-spot thickness or automated.

PREVAC SCIENTEC

17 avenue des Andes – Bât. Le Cèdre
91940 Les Ulis (France)
+33 (0)1 64 53 27 00
info@scientec.fr
www.scientec.fr

SINDLHAUSER MATERIALS

Stand # 03

Sindlhauser Materials GmbH is an internationally active company that specializes in the manufacture and sale of materials and components for PVD coating processes. The product range includes sputtering targets, oxide and non-oxide ceramics, LaB_6 cathodes, suspensions, granulates, evaporation materials and components made of tungsten, tantalum and molybdenum. The portfolio also includes specialized oils and lubricants for vacuum pumps. In addition to manufacturing, Sindlhauser Materials also offers services such as consulting, product development, target bonding and recycling.
Sindlhauser prioritizes sustainability and resource efficiency, implementing a comprehensive take-back and recycling program to recover valuable materials. Research and development play an important role. For example, the company has developed innovative products such as the high-performance absorber PeroLab® and high-purity Ru-targets as a cost-effective alternative to Au.
The company supplies demanding industries worldwide such as semiconductor production, glass, packaging and decoration, sensor technology, optics, lighting technology and manufacturers for applications in the fields of medical technology, autonomous systems and modern display technologies.
Our team is eager to exchange ideas with you and committed to delivering expert advice and reliable support.

SINDLHAUSER MATERIALS ®

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87437 Kempten (Germany)
+49 (0)831 960 458 74
schmoll@sindlhauser.de
www.sindlhauser.de

SOLCERA

Stand # 21

Solcera: Expertise in advanced ceramics for vacuum and ultra-high vacuum
With a 200-year heritage in advanced ceramics and more than 50 years of experience in brazed hermetic assemblies, Solcera is a leader in solutions for vacuum and ultra-high vacuum applications. Its technical ceramics, ceramic-to-metal and glass-metal assemblies guarantee high-level of sealing, essential for demanding environments such as aerospace, nuclear, scientific research and particle accelerators.
Solcera operates from two sites in France and is strengthening its international presence through subsidiaries in Brazil and Germany and a sales office in Spain. In close collaboration with its customers, Solcera develops customized solutions, from prototyping to volume production, thanks to recognized expertise and a capacity for constant innovation.

SOLCERA
Advanced Materials

83 rue Marcelin Berthelot
77550 Moissy-Cramayel (France)
+33 (0)2 32 29 42 21
info@solcera.com
www.solcera.com

SPM AG

Stand # 07

SPM delivers comprehensive semiconductor solutions that enhance your production efficiency through specialized sputtering target bonding services, high-quality spare parts, and technical support. Your manufacturing benefits from reduced costs, improved yields, and lower total cost of ownership through established partnerships with leading global material manufacturers.
With facilities in Liechtenstein and Croatia since 2018, SPM ensures reliable delivery times across Europe. The Croatian operation provides import, storage, and distribution services alongside bonding capabilities, offering complete support for EU manufacturers.
The proprietary bonding technology, developed in Japan, features a unique pre-wetting technique that works completely material-independent without requiring metallization. This ensures consistent, stable quality for your production needs. Every process is fully customized—from material selection through bonding and backing plate specifications—tailored to your unique requirements.
Continuous innovation introduces new materials and solutions that optimize your production processes. Through close collaboration between suppliers and manufacturers, SPM delivers measurable results that strengthen your competitive position in the semiconductor market while addressing your specific manufacturing challenges.

spm

Benderertrasse 29
9494 Schaan (Liechtenstein)
+385 99 537 6983
andrea@spm.li
www.spm.li

SURCOTEC

Stand # 14

Surcotec SA, founded in 1995 in Plan-les-Ouates (Geneva, Switzerland), is a specialist in vacuum coating and surface engineering. With strong expertise in PVD, PECVD, and ALD technologies, the company develops coatings that combine aesthetics and performance for a wide range of demanding applications.
One of its key markets is Swiss watchmaking, where Surcotec delivers decorative and protective layers that enhance durability, color stability, and the luxury finish of timepieces. Beyond horology, the company serves multiple industries including micro-engineering, optics, medical devices, and aerospace. This versatility highlights Surcotec's ability to adapt advanced coating technologies to very diverse technical and design requirements.

Its offer covers the entire value chain: from surface preparation and coating deposition to industrial analysis and system design. Surcotec also invests in large-scale capabilities, such as Surcoflex, a roll-to-roll vacuum coating unit launched in 2016 to address high-volume and flexible manufacturing needs.
In addition, the company provides analytical services, including SEM-EDX microscopy and contaminant testing, supporting quality assurance and industrial safety. By combining cutting-edge surface engineering with cross-sector expertise, Surcotec has built a solid reputation as a reliable Swiss partner for innovation, precision, and long-term collaboration.

SURCOTEC
SURFACE COATING TECHNOLOGY

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1228 Plan-les-Ouates, Geneva
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+41 22 794 73 83
web@surcotec.ch
www.surcotec.ch

TESTBOURNE BV

Stand # 25

Testbourne is a leading supplier of materials and instruments for Industries and Research & Development.
we have over 45 years of experience with metals, alloys and compounds.
Testbourne supplies an extensive selection of materials available in fabricated forms including sputtering/arc targets, evaporation materials, powders, wire, rods & sheets.
For your evaporation requirement we also supply evaporation sources, multi-strand filaments, wire baskets, boats and crucibles.
We supply our materials in a variety of markets, including:

- Glass Coatings: Providing advanced materials for innovative glass coating technologies.
- Decorative & Hard-Wearing Coatings: Enabling the production of aesthetically pleasing and durable coatings.
- Electronics: Supplying critical materials for electronic components and devices.
- Energy: Supporting sustainable energy solutions with high-performance materials.
- Defence: Offering specialised materials for high-stakes defense applications.
- Semiconductors: Supplying precision materials crucial for semiconductor manufacturing.
- Government Research Establishments & Universities: Partnering with academic and research institutions to drive scientific advancements.

Testbourne is more than a supplier – we are your trusted partner in material science solutions. Our expertise, commitment to quality and dedication to customer success set us apart.

Testbourne

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www.testbourne.com

VAT

Stand # 16

We change the world with vacuum solutions – that is our purpose as the world's leading supplier of high-end vacuum valves. The Group reports in two segments: Valves and Global Service. The Valves segment is a global developer, manufacturer and supplier of vacuum valves for the semiconductor, displays, photovoltaics and vacuum coating industries as well as for the industrial and research sector. Global Service provides local expert support to customers and offers genuine spare parts, repairs and upgrades. In 2024, VAT employs some 3,200 people worldwide, with representatives in 29 countries and manufacturing sites in Switzerland, Malaysia, and Romania.

26 avenue Jean Kuntzmann
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PLATHINIUM

PLASMA THIN FILM INTERNATIONAL UNION MEETING

See you for the 5th edition

20 - 24 September 2027

Antibes, French Riviera

www.plathinium.com

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PLATHINIUM
PLASMA THIN FILM INTERNATIONAL UNION MEETING

22-26 September 2025 / Antibes (France)

Overview program

Monday 22 Sept.

8:30 - 9:10 — Short course Registration / Badge pick up

9:00 - 10:40 — Tutorial #1 — *T. Belmonte*

9:25 - 10:05

10:05 - 10:35 — *Coffee break 20'*

10:35 - 10:55

10:55 - 11:15

11:00 - 12:40 — Tutorial #2 — *U. Cvelbar*

11:15 - 11:35

11:35 - 11:55

11:55 - 12:15

12:30 - 14:00 — Lunch

14:00 - 14:40

14:20 - 16:00 — Tutorial #3 — *R. Dussart*

14:45 - 15:05

15:05 - 15:25

15:25 - 15:45

15:45 - 16:15 — *Coffee break 20'*

16:15 - 16:45

16:20 - 18:00 — Tutorial #4 — *R. van de Sanden*

16:45 - 17:05

17:05 - 17:25

17:25 - 17:45

17:45 - 18:05

18:00 - 18:20

18:30 - 20:00 — **Registration/Badge pick up & Welcome reception** *until 20:00*

EXHIBITION SET UP

Tuesday 23 Sept.

Antipolis Auditorium

8:30 - 9:10 — Registration / Badge pick up

9:10 - 9:25 — Opening ceremony

9:25 - 10:05 — **PL1 / M. SANKARAN**

10:05 - 10:35 — *Coffee break 30'*

10:35 - 10:55	DEPO1-01-077 L. Villibord	DEPO 1/7	AMELI1-01-038 T. Czerwiec	AMELI 1/2
10:55 - 11:15	DEPO1-02-031 Y. Wang		AMELI1-02-016 C. Boudat	
11:15 - 11:35	DEPO1-03-023 F. Ahangarani-Farahani		AMELI1-03-103 T.S. Nguyen	
11:35 - 11:55	DEPO1-04-123 S-E. Benrazzouq		AMELI1-04-102 S. Mouchtouris	
11:55 - 12:15	DEPO1-05-035 J. Carneiro de Oliveira		AMELI1-05-112 A.M. Lanza	

12:30 - 14:00 — Lunch *(from 12:30)*

14:00 - 14:40 — **PL2 / M. CREATORE**

14:45 - 15:05	GROM1-01-022 D. Babonneau	GROM 1/2	PSURF1-01-075 A. Tavernier	PSURF 1/5
15:05 - 15:25	GROM1-02-117 N. Fosseur		PSURF1-02-104 H. Beji	
15:25 - 15:45	GROM1-03-130 L. Zajickova		PSURF1-03-046 R. Dussart	

15:45 - 16:15 — *Coffee break 30'*

16:15 - 16:45	GROM2-K1-045 A-L. Thomann	GROM 2/2	PSURF2-K1-090 S. Hamaguchi	PSURF 2/5
16:45 - 17:05	GROM2-01-005 A. Besnard		PSURF2-01-107 G. Kokkoris	
17:05 - 17:25	GROM2-02-108 C. Mastail		PSURF2-02-049 A. Rahali	

17:25 - 18:20 — **Poster session I** *(from 17:30 until 19:30)* **&** **Industrial evening** *(from 18:30 until 20:30)*

EXHIBITION

Wednesday 24 Sept.

Antipolis Auditorium

8:30 - 9:10 — **PL3 / A. LIETZ**

9:10 - 9:25	DEPO2-01-121 P. Abarca	DEPO 2/7	MODIDD1-01-070 D. Stefas	MODIDD 1/4
9:25 - 10:05	DEPO2-02-067 P. Zeman		MODIDD1-02-019 A. Patelli	

10:05 - 10:35 — *Coffee break 30'*

10:35 - 10:55	DEPO3-01-047 G. Chettouh	DEPO 3/7	MODIDD2-01-024 Y. Song	MODIDD 2/4
10:55 - 11:15	DEPO3-02-083 T. Nguyen		MODIDD2-02-093 Y. Agha	
11:15 - 11:35	DEPO3-03-131 J-F. Pierson		MODIDD2-03-082 T. Silva	
11:35 - 11:55	DEPO3-04-115 L. Marcinauskas		MODIDD2-04-097 S. Chouteau	
11:55 - 12:15	DEPO3-05-057 D. Kalanov		MODIDD2-05-099 S. Kim	

12:30 - 14:00 — Lunch *(from 12:30)*

14:00 - 14:40 — **PL4 / R. ONO**

14:45 - 15:05	AMELI2-01-055 A. Bousquet	AMELI 2/2	ITEC1-01-048 D. Bensalem	ITEC 1/3
15:05 - 15:25	AMELI2-02-058 S. Konstantinidis		ITEC1-02-015 E. Haye	
15:25 - 15:45	AMELI2-03-030 A. Diop		ITEC1-03-006 L. Valera	
15:45 - 16:15	AMELI2-04-080 J. Purans		ITEC1-04-139 S. Böhm	

16:15 - 16:45 — *Coffee break 30'*

16:45 - 18:20 — **Poster session II** *(from 16:35 until 18:30)*

EXHIBITION

DISMANTLING

Thursday 25 Sept.

Antipolis Auditorium

8:30 - 9:10 — **PL5 / M. BILEK**

9:10 - 9:25	DEPO4-01-004 D. Hegemann	DEPO 4/7	PSURF3-01-033 D. Manova	PSURF 3/5
9:25 - 10:05	DEPO4-02-040 M. Troia		PSURF3-02-029 M. Sikiric	

10:05 - 10:35 — *Coffee break 30'*

10:35 - 10:55	DEPO5-01-092 M. Ezzehar	DEPO 5/7	PSURF4-01-001 P. Chapon	PSURF 4/5
10:55 - 11:15	DEPO5-02-109 A. Culot		PSURF4-02-105 T.C. Mbouja Signe	
11:15 - 11:35	DEPO5-03-110 R. Costes		PSURF4-03-122 S.S. Kim	
11:35 - 11:55	DEPO5-04-020 P. Covin		PSURF4-04-111 D. Pjević	
11:55 - 12:15	DEPO5-05-039 L. Janu		PSURF4-05-026 M. Segers	

12:30 - 14:00 — Lunch *(from 12:30)*

14:00 - 14:40 — **PL6 / J. ALAMI**

14:45 - 15:05	PSURF5-01-007 L. Zahedi	PSURF 5/5	MODIDD3-01-113 T. Minea	MODIDD 3/4
15:05 - 15:25	PSURF5-02-114 R. Dantinne		MODIDD3-02-054 M. Farahani	
15:25 - 15:45	PSURF5-03-124 J-F. Coulon		MODIDD3-03-037 P. Vasina	

15:45 - 16:15 — *Coffee break 30'*

16:15 - 16:45	DEPO6-01-042 B. Menacer	DEPO 6/7	MODIDD4-01-021 A. Hellé	MODIDD 4/4
16:45 - 17:05	DEPO6-02-116 S. Calvez		MODIDD4-02-088 P. Vinchon	
17:05 - 17:25	DEPO6-03-051 L. Coelho		NANO1-01-028 A. Aryan	NANO 1/2
17:25 - 17:45	DEPO6-04-120 M. Roggio		NANO1-02-076 J. Capek	
17:45 - 18:05	DEPO6-05-061 S. Rubio		NANO1-03-086 M. Gireau	
18:00 - 18:20			NANO1-04-052 N. Jacquot	

18:30 - 20:00 — **Conference dinner cocktail** *from 19:30*

Friday 26 Sept.

Antipolis Auditorium

8:30 - 9:10 — **PL7 / O. GUAITELLA**

9:10 - 9:25	ITEC2-01-135 R. van de Sanden	ITEC 2/3	DEPO7-01-091 S. Hekking	DEPO 7/7
9:25 - 9:45	ITEC2-02-034 C. Costin		DEPO7-02-106 R. Del Sole	

9:45 - 10:05 — *Coffee break 30'*

10:05 - 10:35	ITEC3-K1-125 R. Snyders	ITEC 3/3	NANO2-K1-010 A. Granier	NANO 2/2
10:35 - 10:55	ITEC3-01-044 J. Barbé		NANO2-01-069 H. Klein	
10:55 - 11:15	ITEC3-02-084 U. Cvelbar		NANO2-02-041 M. Costes	
11:15 - 11:35	ITEC3-03-078 O. Touré		NANO2-03-018 H. Gerami	

11:45 - 12:10 — Closing ceremony

12:10 - 12:25

12:25 - 18:15 — **Social Activities (excursions)** *until 18:00*

EXHIBITION

DISMANTLING

Topics: AMELI, GROM, MODIDD, DEPOS, NANO, PSURF, ITEC

Poster sessions, exhibition, coffee breaks & lunches are located in the Gould area

update on 01/09/2025